

Analyses of Diamond Disc Substrate Wear and Diamond Micro-Wear in Copper Chemical Mechanical Planarization Process

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Outline

1. Motivations

2. Objectives & approaches

3. Static etch test results

- SEM analysis
- ICPMS analysis
- Interferometric analysis

4. Wear test results

- SEM analysis
- Interferometric analysis
- Pad wear rate analysis

5. Summary

Motivations

There is strong evidence of diamond disc substrate loss and diamond micro-wear during extended copper CMP process.

It is not understood whether substrate loss in copper CMP process is due to chemical effects only or combined chemical and mechanical effects.

Although SEM images can show diamond micro-wear clearly, diamond micro-wear has not been successfully quantified.

Objectives & Approaches

Objectives: investigate diamond disc substrate wear and diamond micro-wear for three types of diamond discs during copper CMP process.

Approaches:

24-hour static etch test at 25 and 50 °C with Cabot Microelectronics Corporation iCue 600Y75 and Fujimi PL-7103 slurries

- **SEM analysis on diamond disc substrate and diamonds**
- **ICPMS analysis on slurry**
- **Interferometric analysis on diamond disc substrate and diamonds**

24-hour wear test on Araca APD-800 polisher at 25 and 50 °C with Cabot Microelectronics Corporation iCue 600Y75 and Fujimi PL-7103 slurries

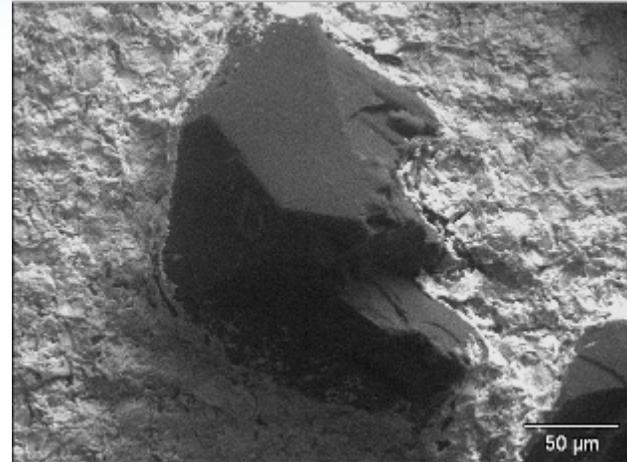
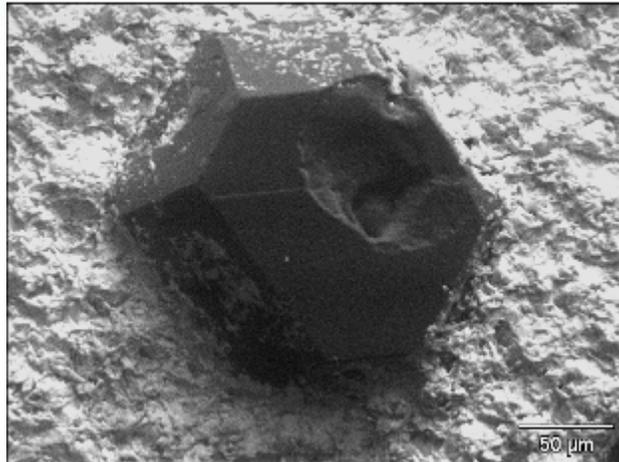
- **SEM analysis on diamond disc substrate and diamonds**
- **Interferometric analysis on individual aggressive diamonds**
- **Pad wear rate analysis**

Static Etch Test Results

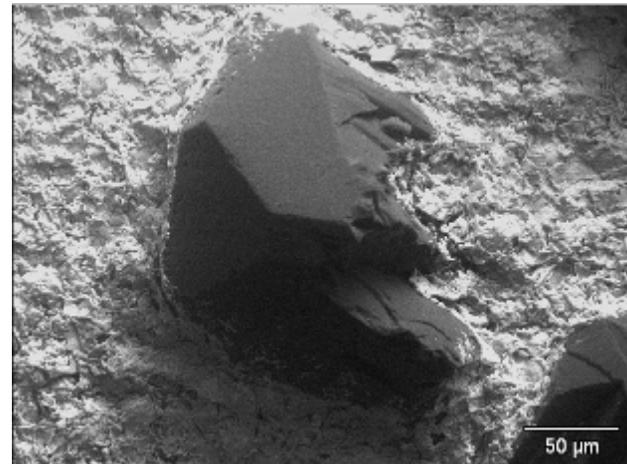
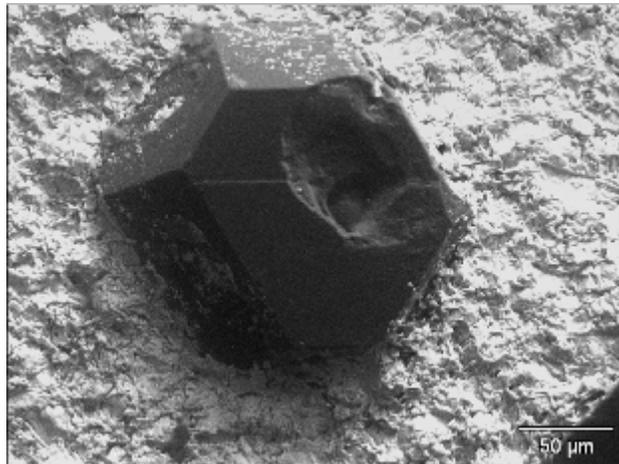
SEM Analysis

D1 with CMC iCue 600Y75 Slurry at 25 °C

Before
Static
Etch
Test



After
Static
Etch
Test

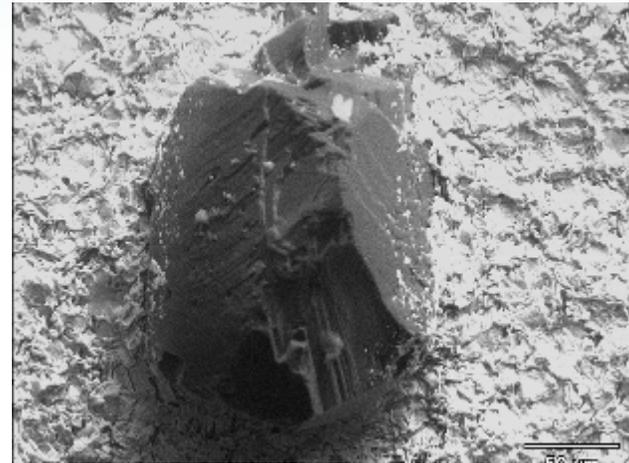
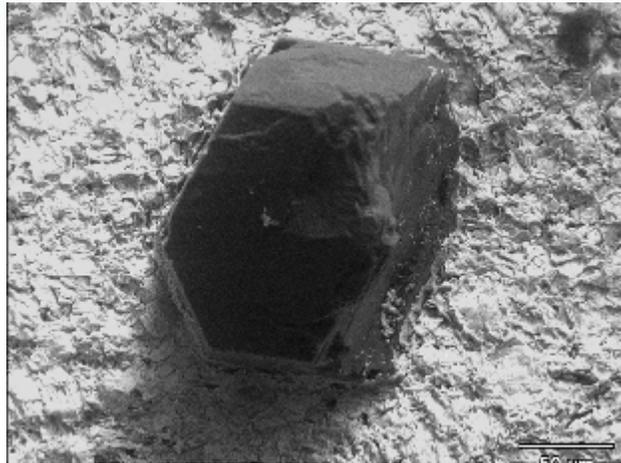


There was no appreciable wear on the diamond disc substrate and diamonds.

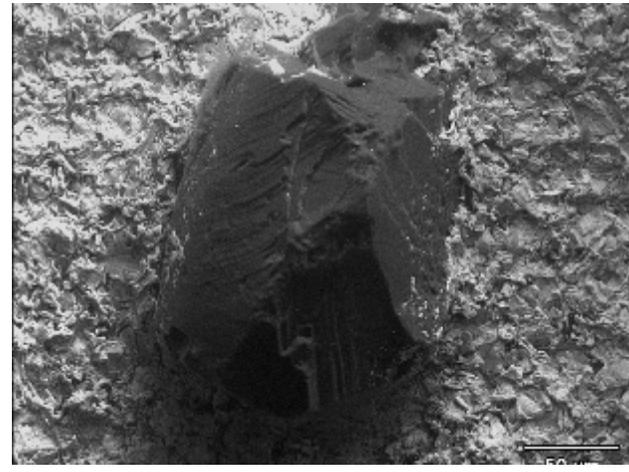
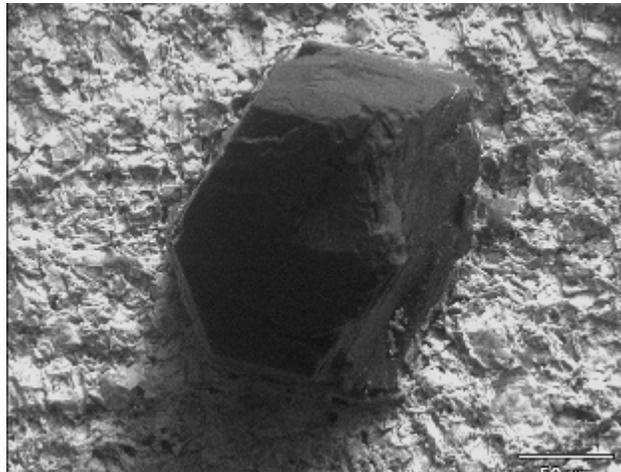
SEM Analysis

D1 with CMC iCue 600Y75 Slurry at 50 °C

Before
Static
Etch
Test



After
Static
Etch
Test

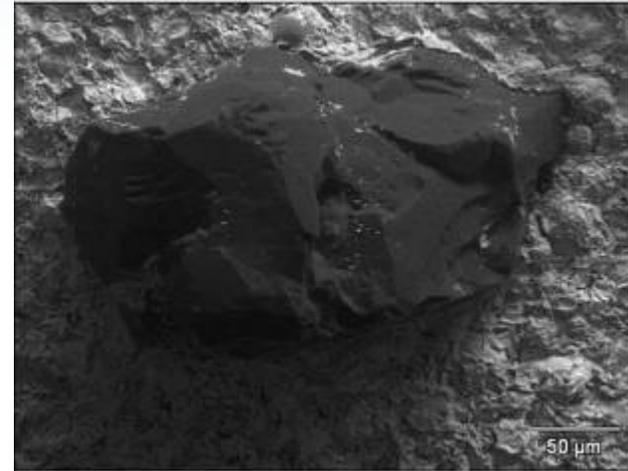
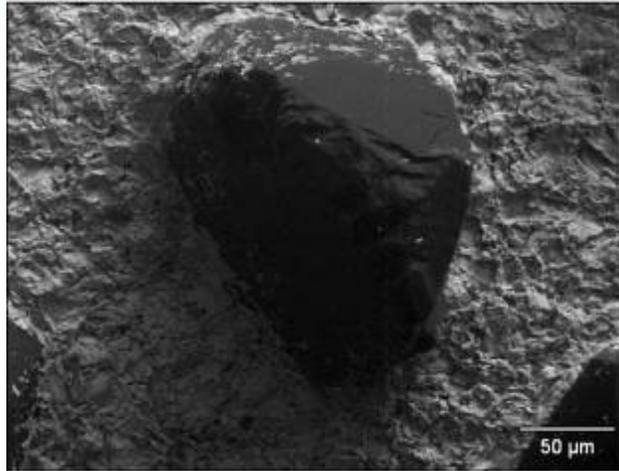


There was no appreciable wear on the diamond disc substrate and diamonds.

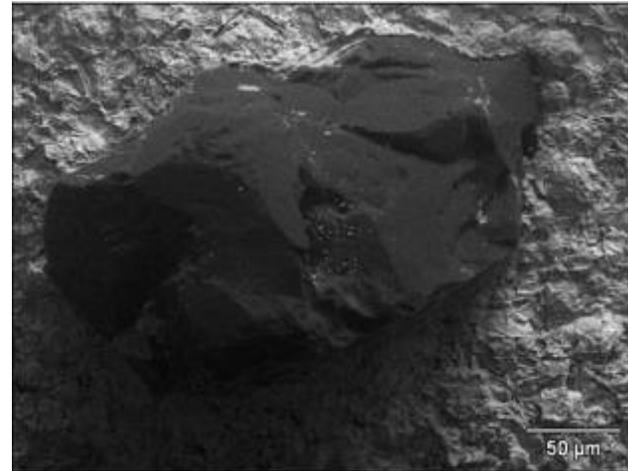
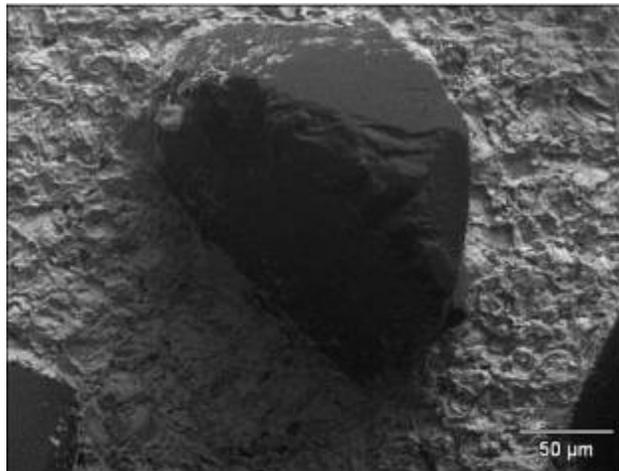
SEM Analysis

D1 with Fujimi PL-7103 Slurry at 25 °C

Before
Static
Etch
Test



After
Static
Etch
Test

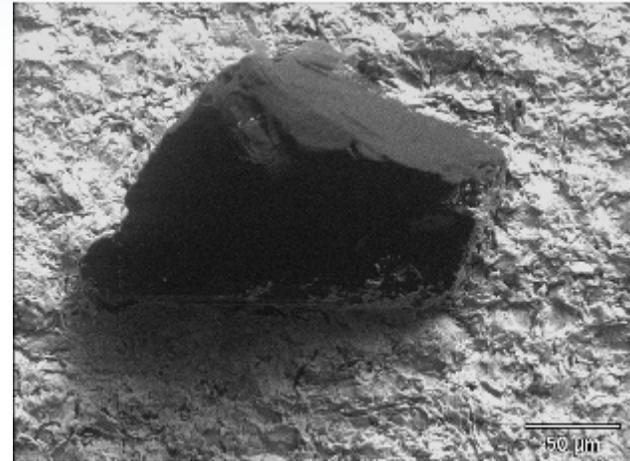
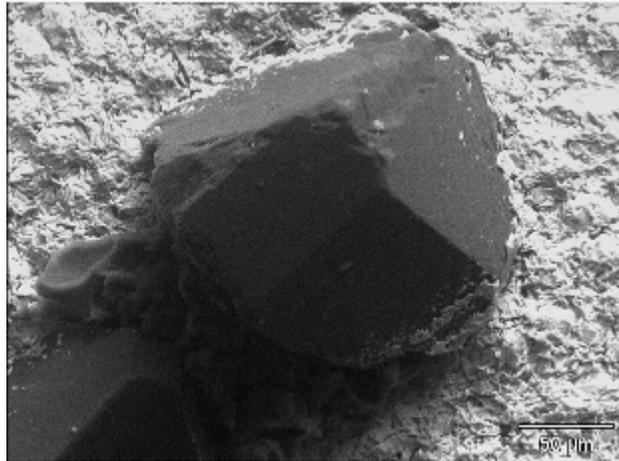


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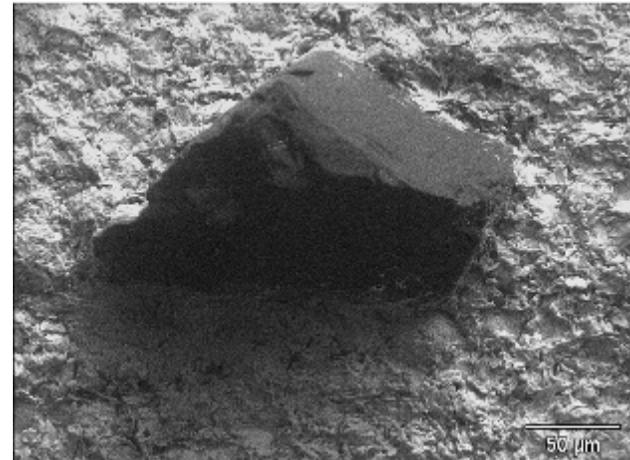
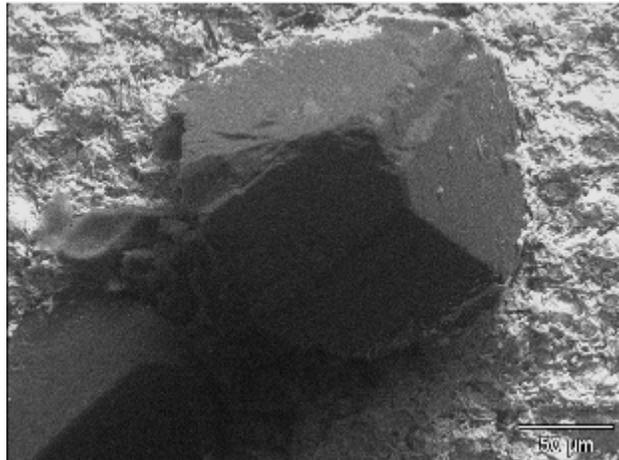
SEM Analysis

D1 with Fujimi PL-7103 Slurry at 50 °C

Before
Static
Etch
Test



After
Static
Etch
Test

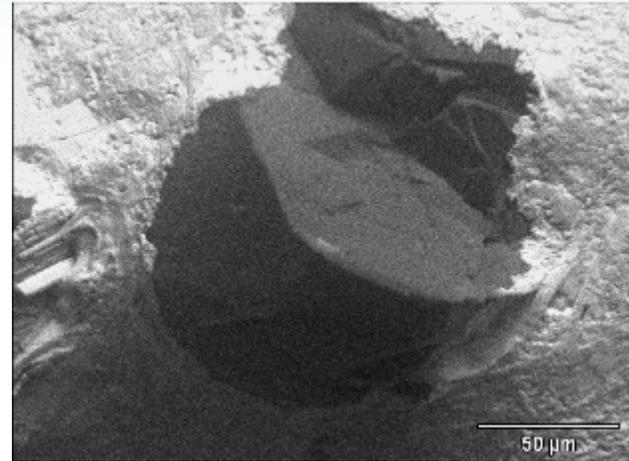
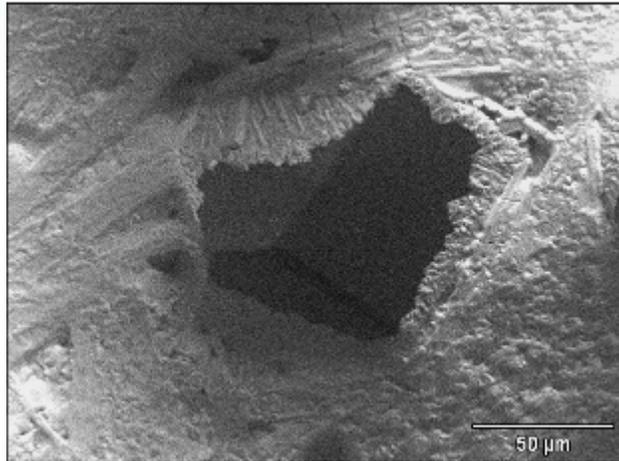


There was no appreciable wear on the diamond disc substrate and diamonds.

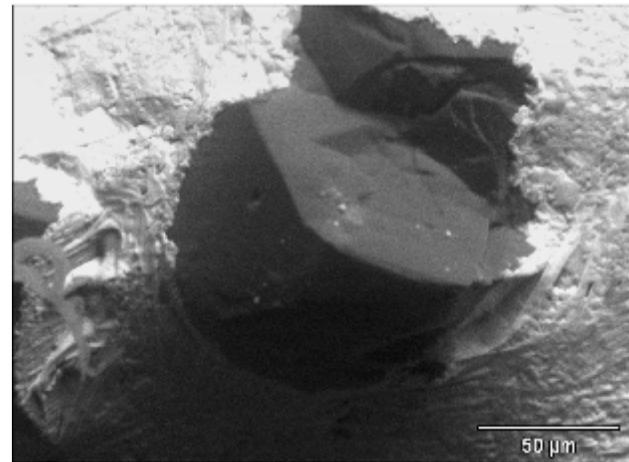
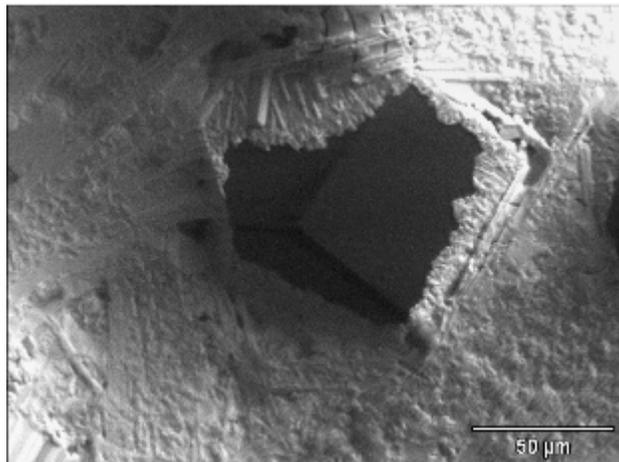
SEM Analysis

D2 with CMC iCue 600Y75 Slurry at 25 °C

Before
Static
Etch
Test



After
Static
Etch
Test

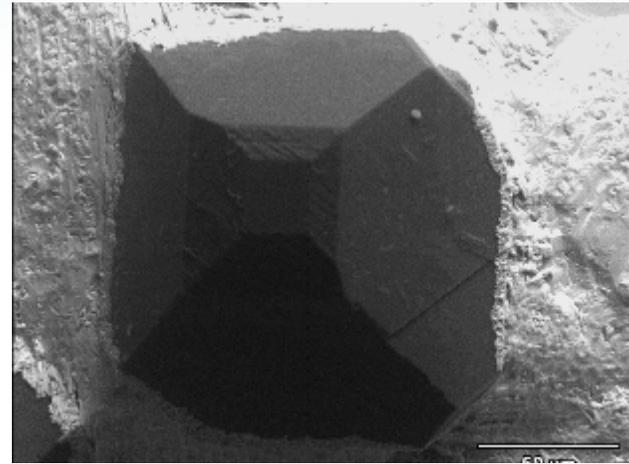
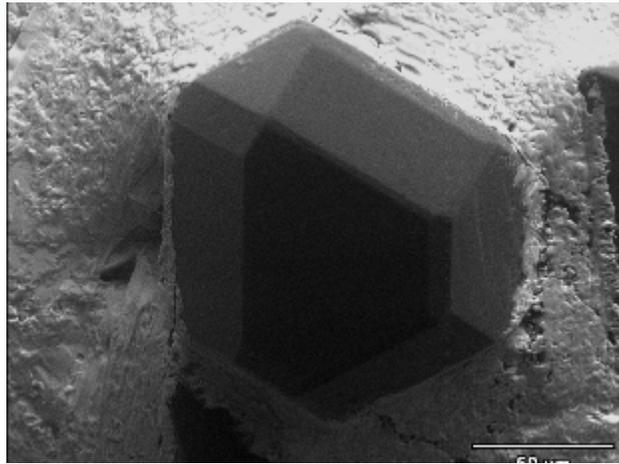


There was no appreciable wear on the diamond disc substrate and diamonds.

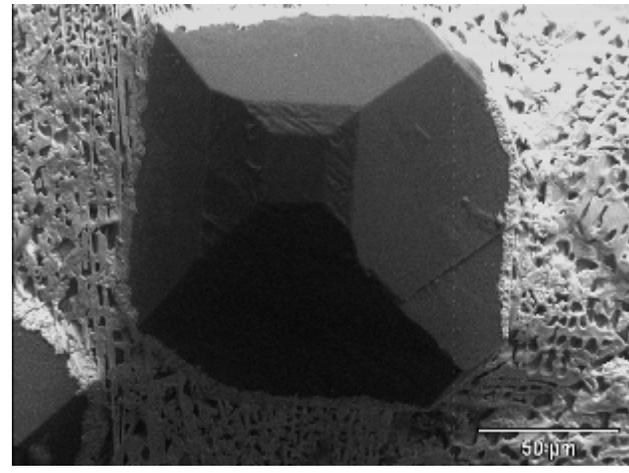
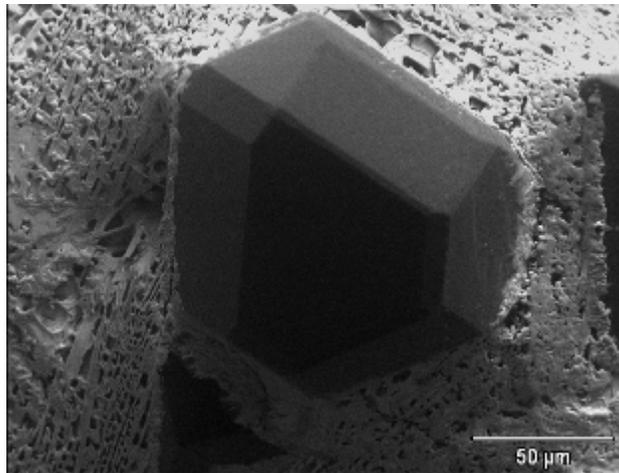
SEM Analysis

D2 with CMC iCue 600Y75 Slurry at 50 °C

Before
Static
Etch
Test



After
Static
Etch
Test

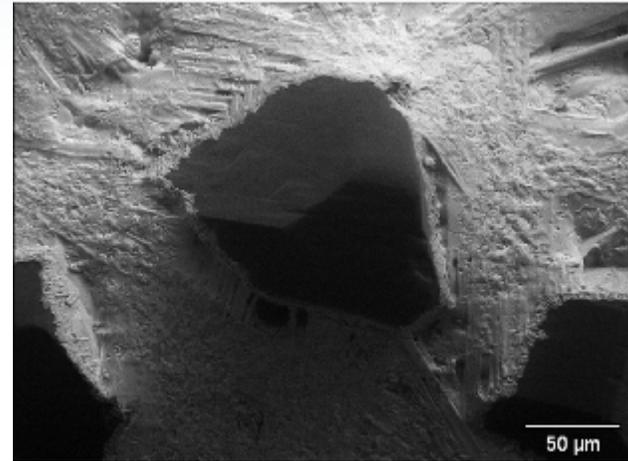
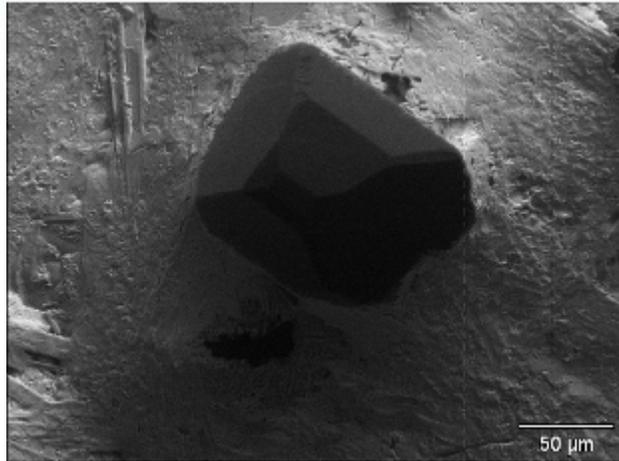


There was apparent surface corrosion on the diamond disc substrate.

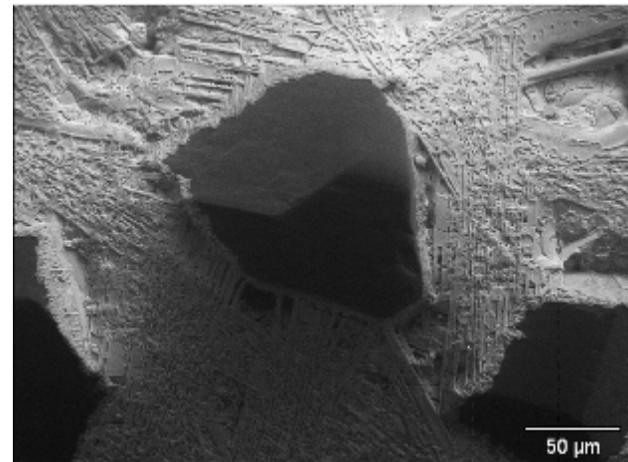
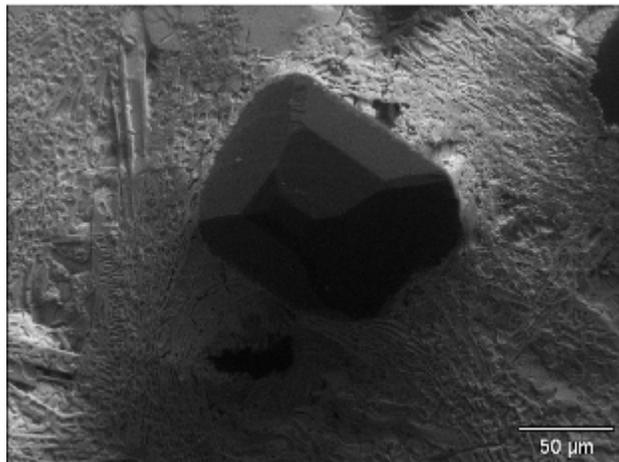
SEM Analysis

D2 with Fijimi PL-7103 Slurry at 25 °C

Before
Static
Etch
Test



After
Static
Etch
Test

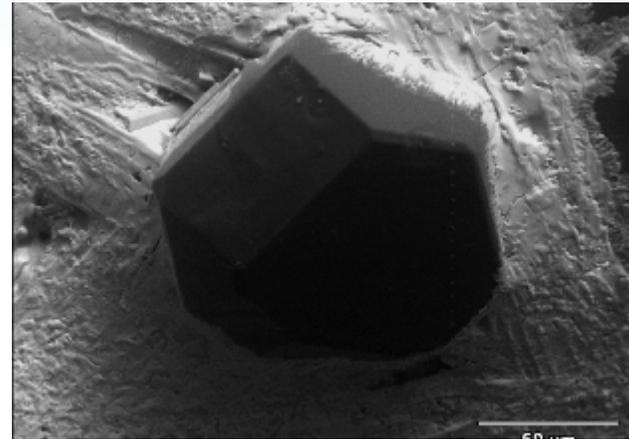
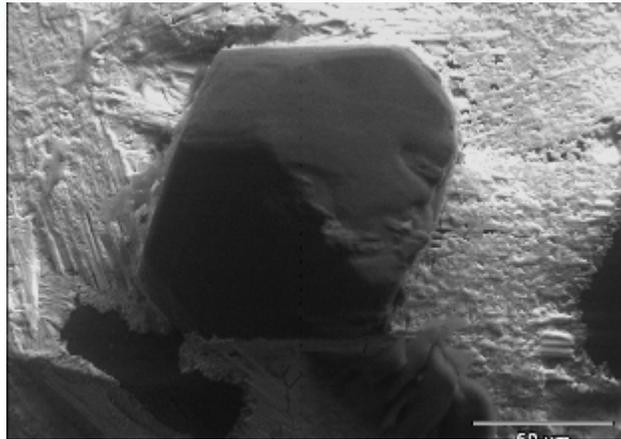


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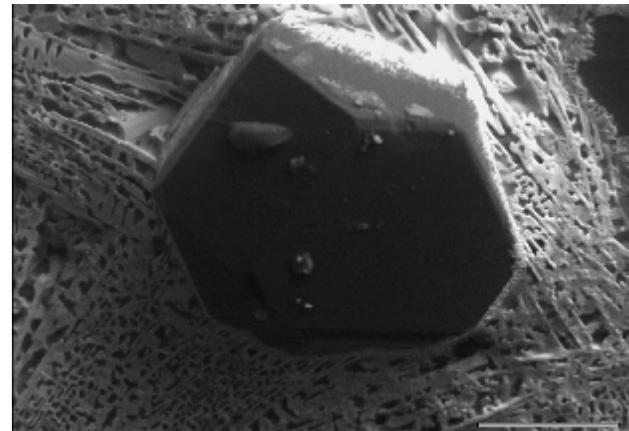
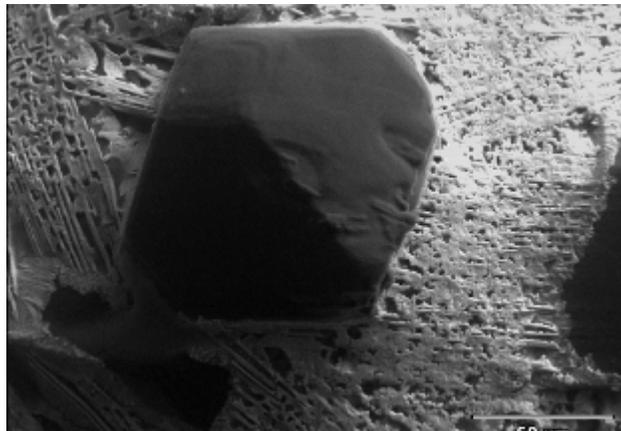
SEM Analysis

D2 with Fijimi PL-7103 Slurry at 50 °C

Before
Static
Etch
Test



After
Static
Etch
Test

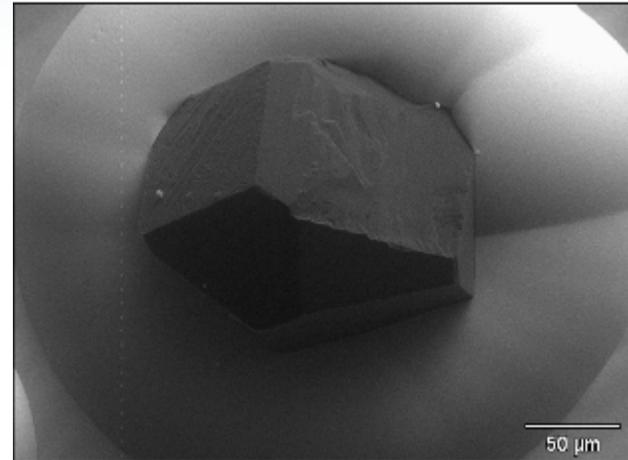
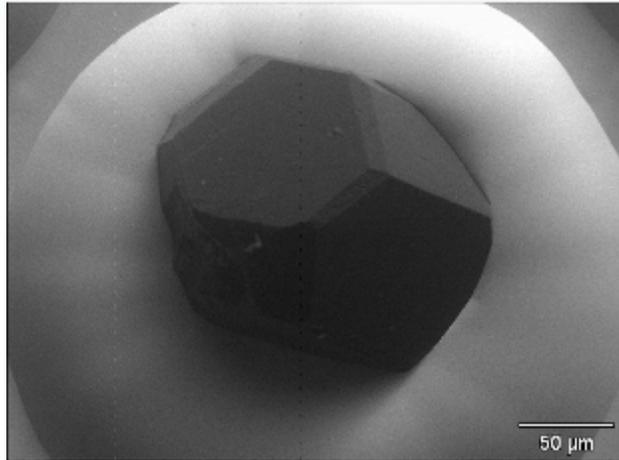


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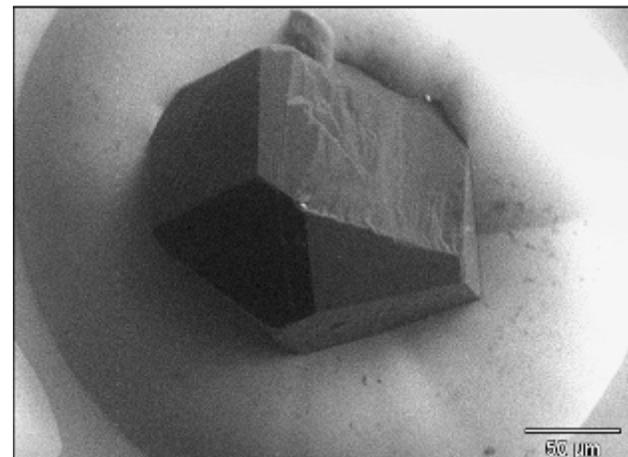
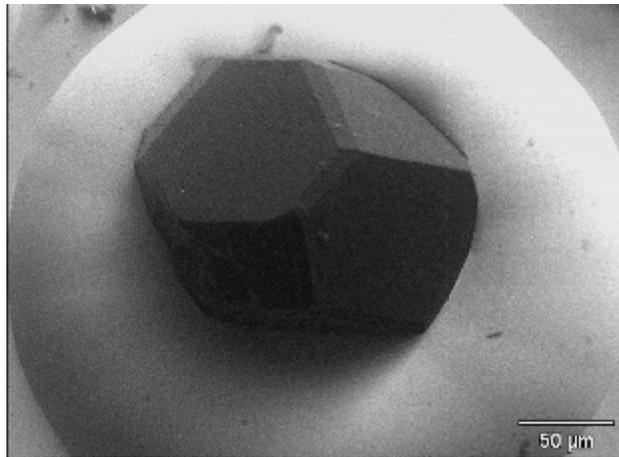
SEM Analysis

D3 with CMC iCue 600Y75 Slurry at 25 °C

Before
Static
Etch
Test



After
Static
Etch
Test

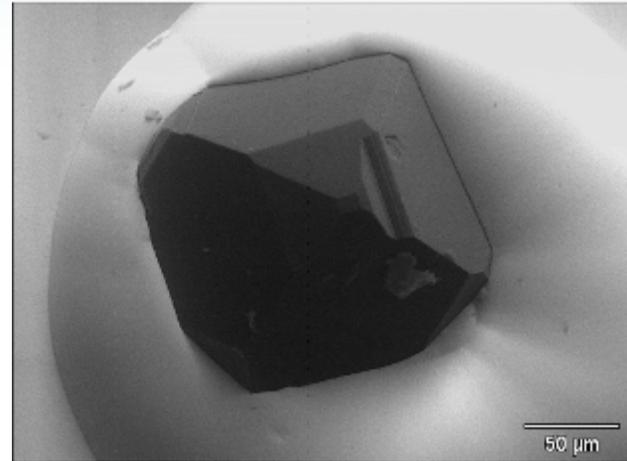
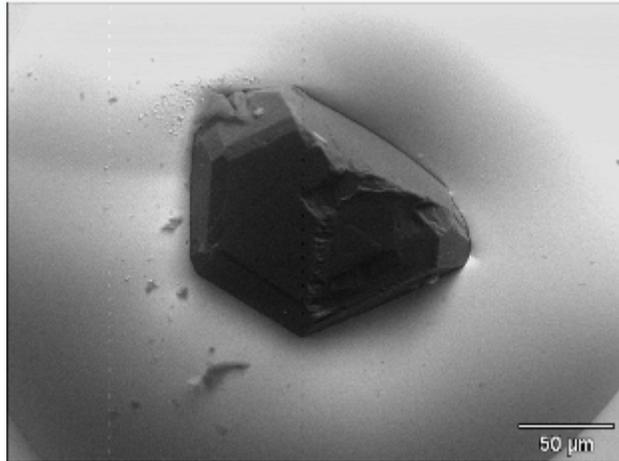


There was no appreciable wear on the diamond disc substrate and diamonds.

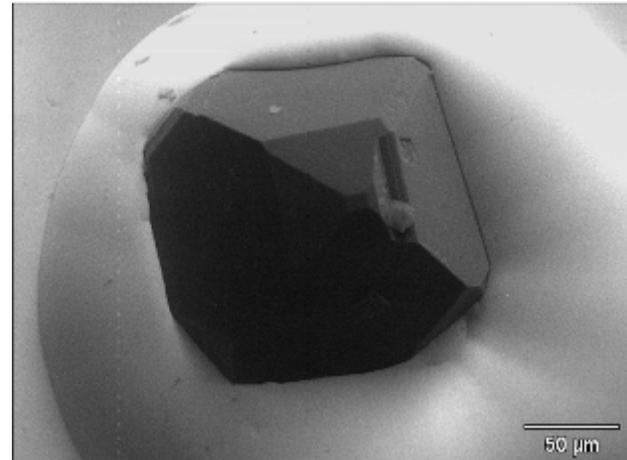
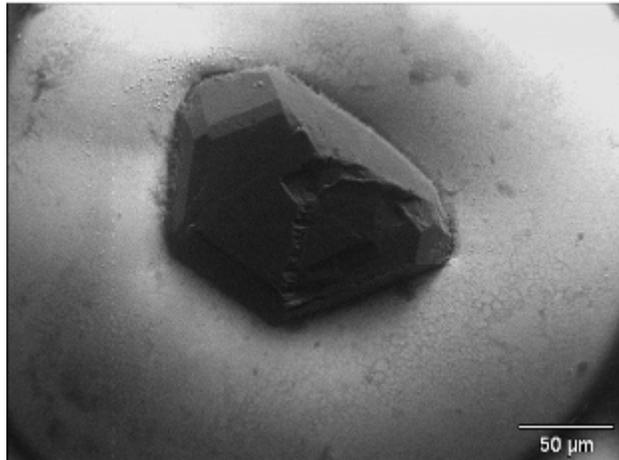
SEM Analysis

D3 with CMC iCue 600Y75 Slurry at 50 °C

Before
Static
Etch
Test



After
Static
Etch
Test

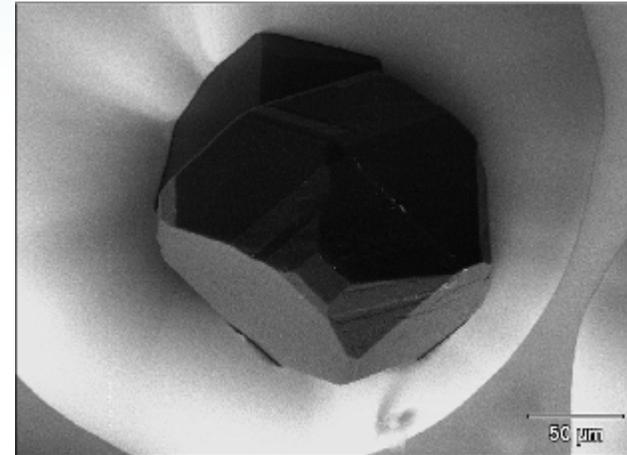
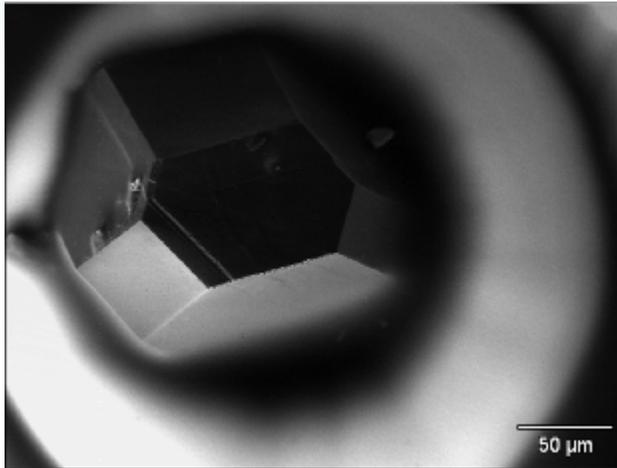


There was no appreciable wear on the diamond disc substrate and diamonds.

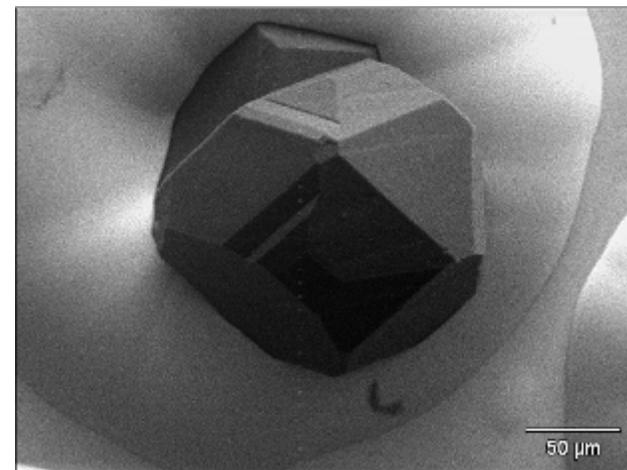
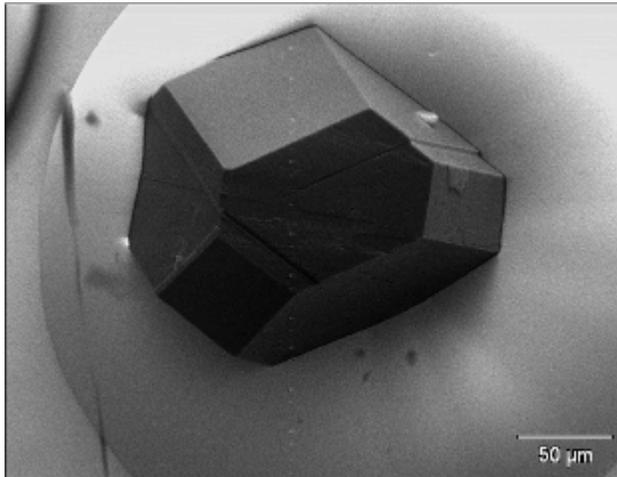
SEM Analysis

D3 with Fujimi PL-7103 Slurry at 25 °C

Before
Static
Etch
Test



After
Static
Etch
Test

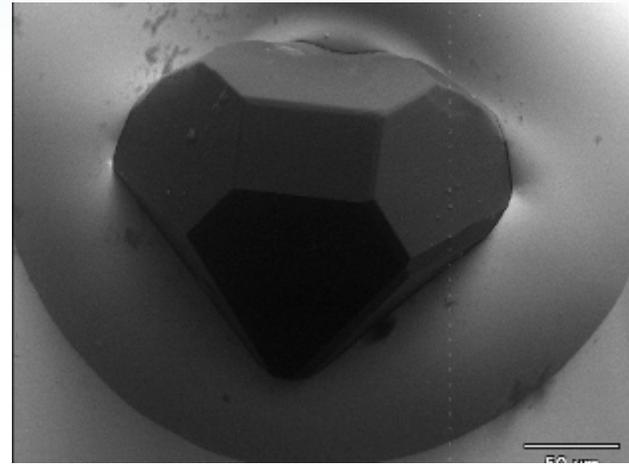
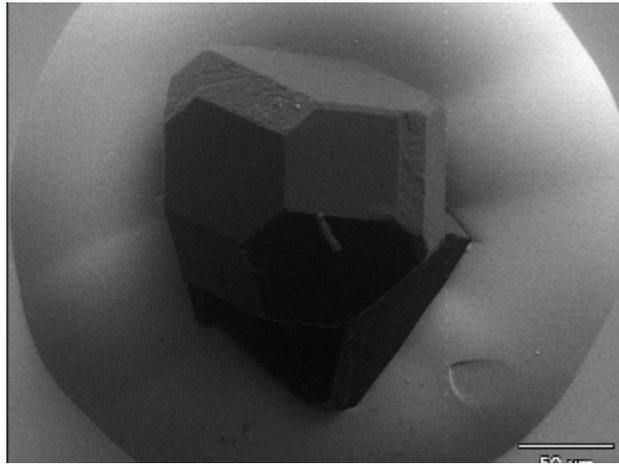


There was no appreciable wear on the diamond disc substrate and diamonds.

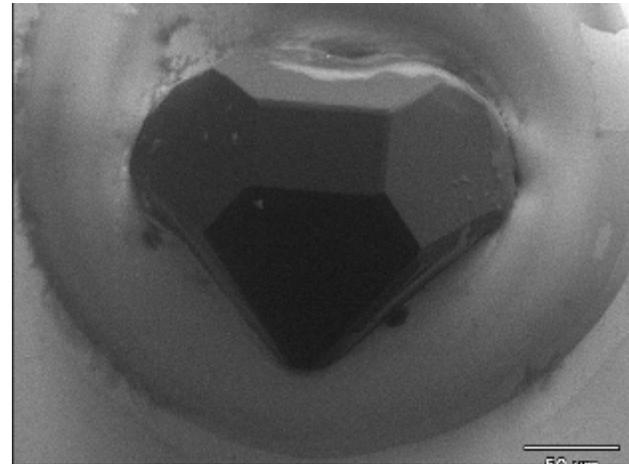
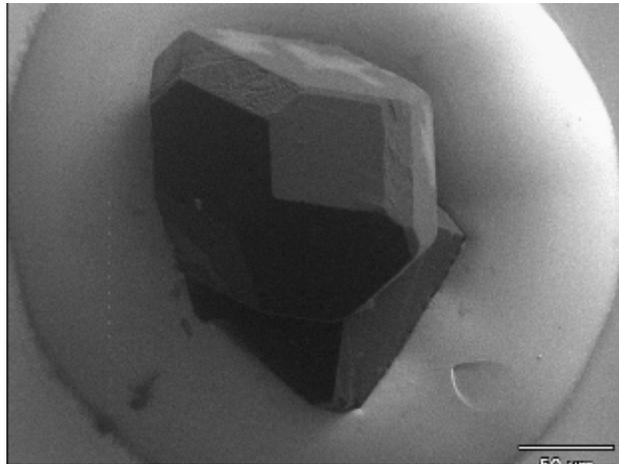
SEM Analysis

D3 with Fujimi PL-7103 Slurry at 50 °C

Before
Static
Etch
Test



After
Static
Etch
Test



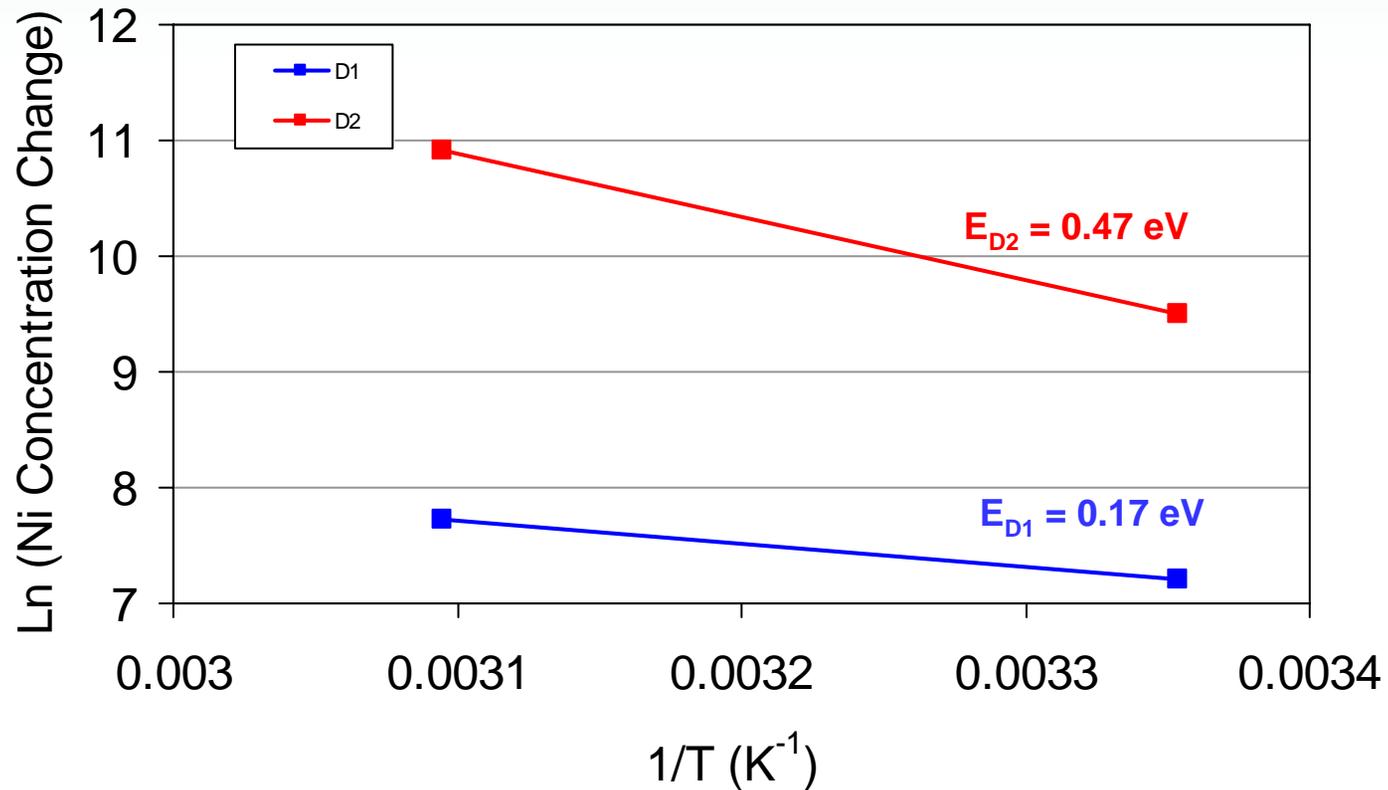
There was no appreciable wear on the diamond disc substrate and diamonds.

ICPMS Analysis – Metal Concentration Changes

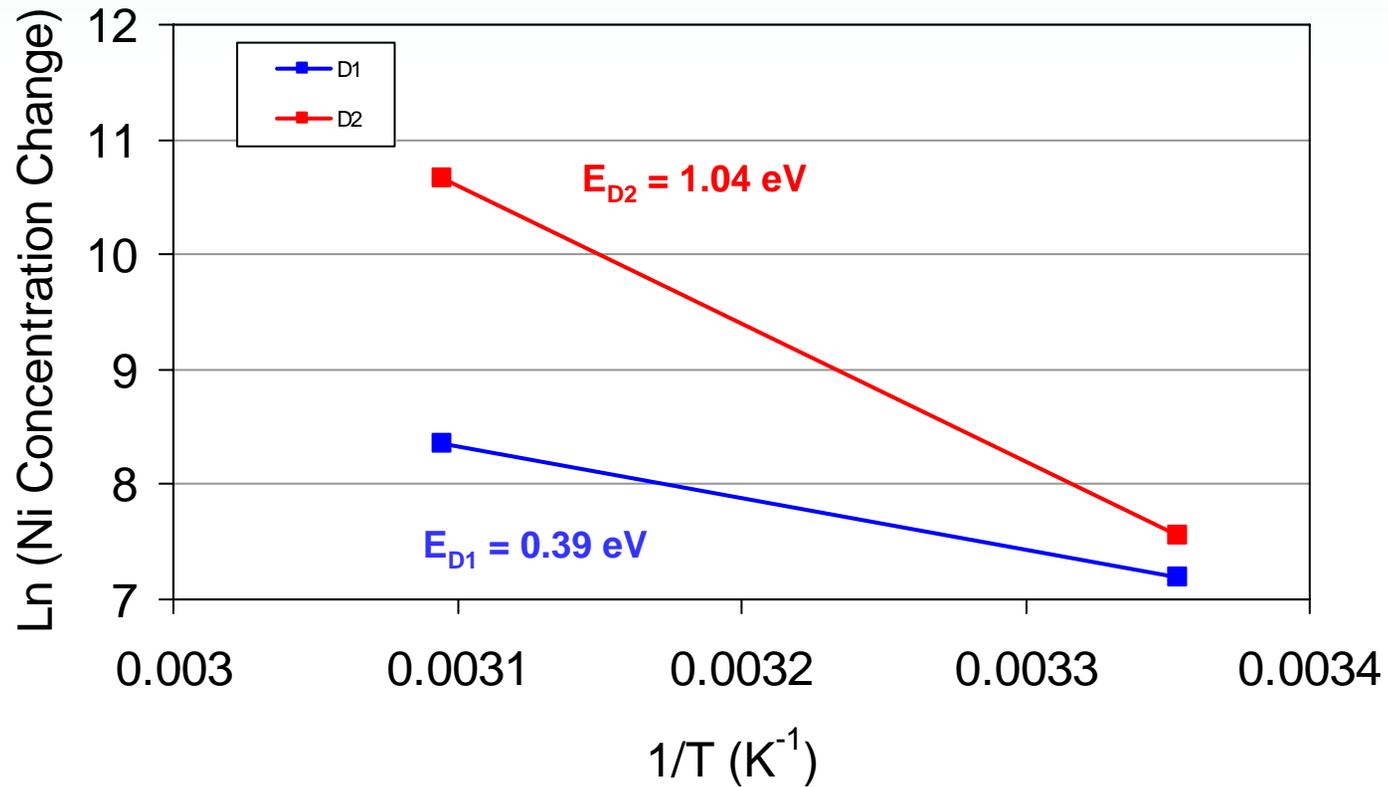
Temperature	Metal	D1 (mg/L)		D2 (mg/L)		D3 (mg/L)	
		Fujimi PL-7103	CMC iCue 600Y75	Fujimi PL-7103	CMC iCue 600Y75	Fujimi PL-7103	CMC iCue 600Y75
25 °C	Ni	1.35	1.33	13.26	1.89	0	0
	Fe	0.03	0	0.44	0.22	0	0
	Cr	0.10	0.07	0.40	0.45	0.02	0.06
50 °C	Ni	2.28	4.25	54.81	42.85	0.06	0.05
	Fe	0	0.07	0.62	1.72	0	0.04
	Cr	0.04	0.13	2.35	2.33	0.02	0.10

Activation Energy of Ni Corrosion

Fujimi PL-7103 Slurry

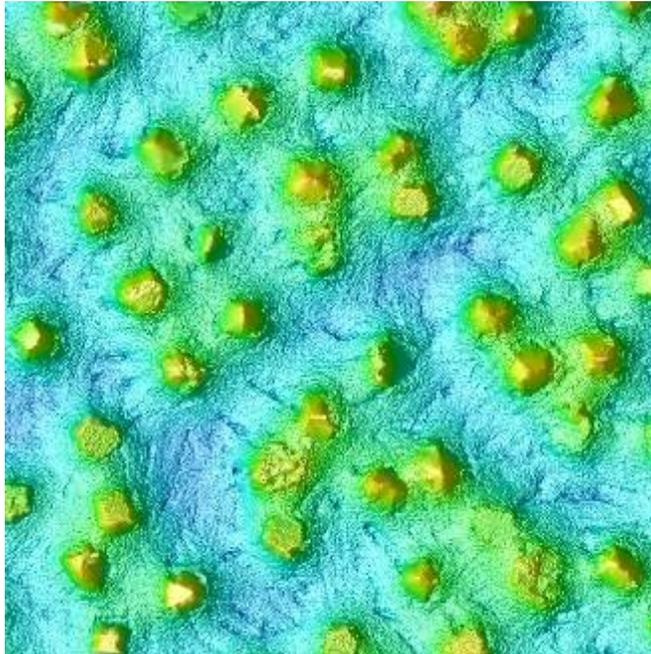


Activation Energy of Ni Corrosion CMC iCue 600Y75 Slurry

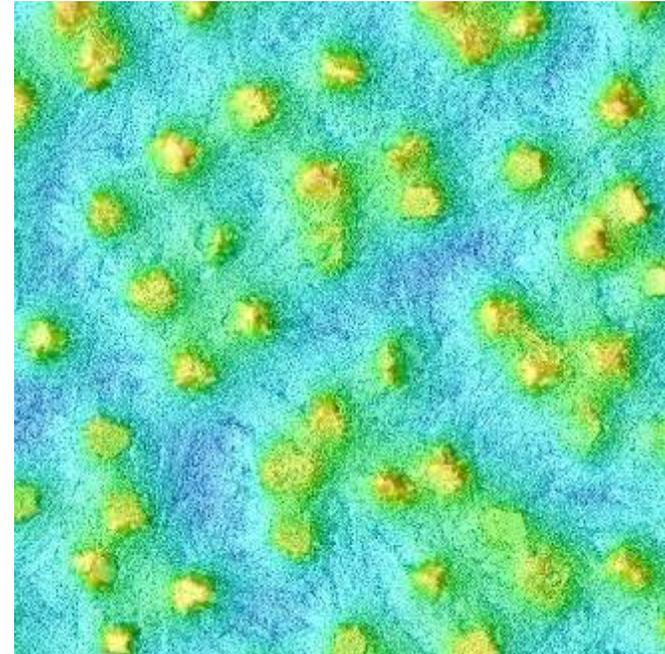


Interferometric Analysis – 2 x 2 mm²

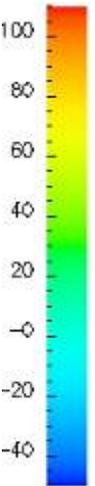
D2 with CMC iCue 600Y75 Slurry at 50 °C



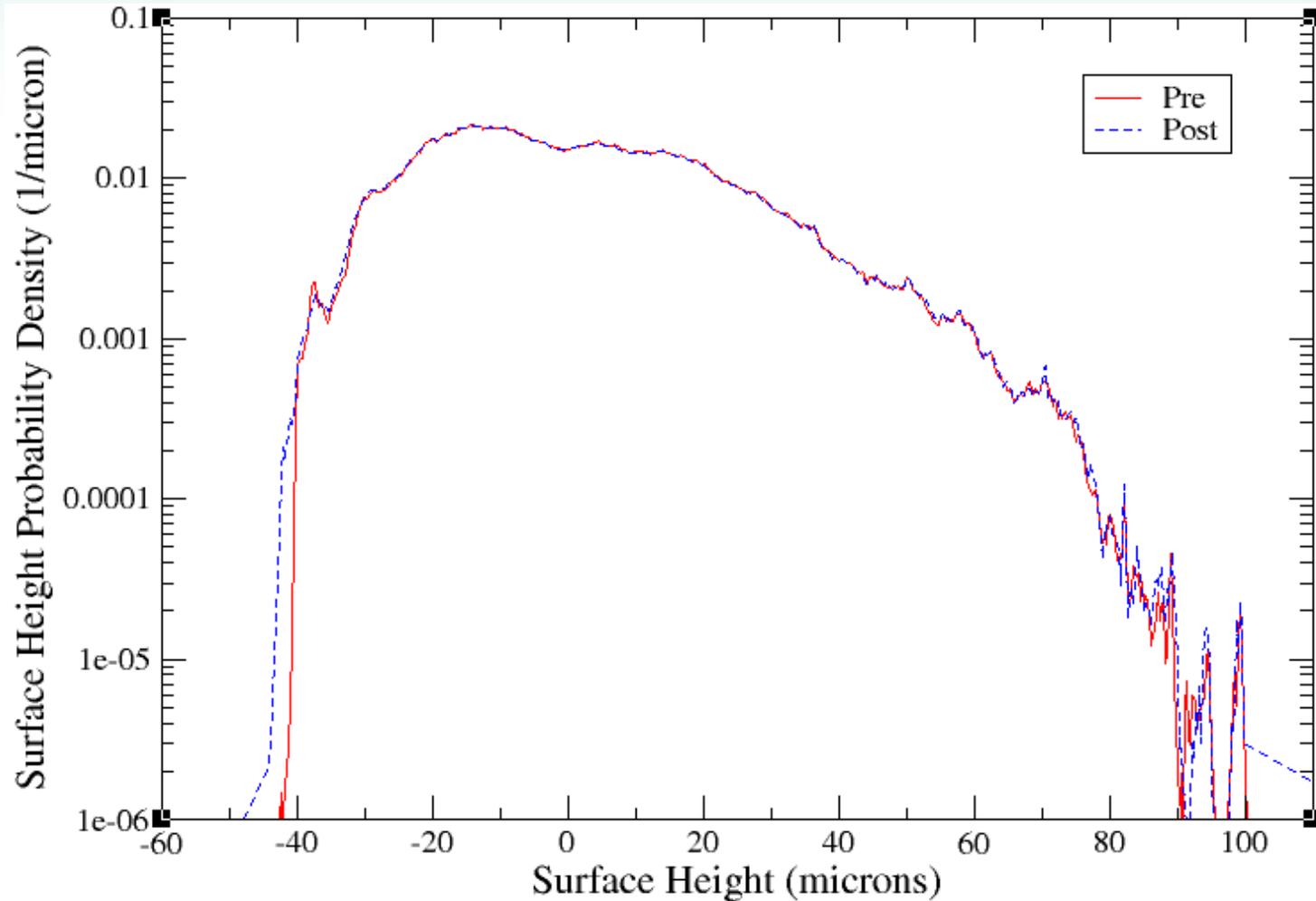
Before Static Etch Test



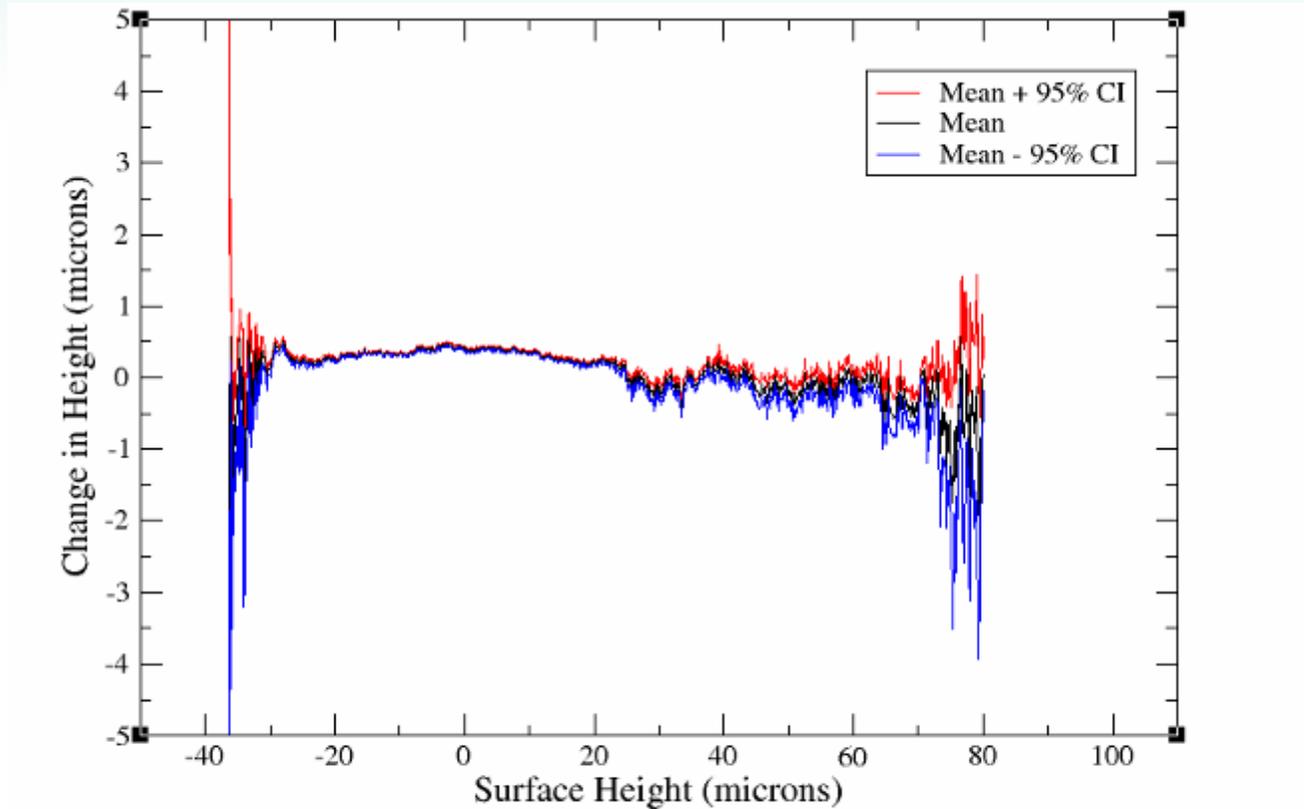
After Static Etch Test



Diamond Disc Surface Height PDFs



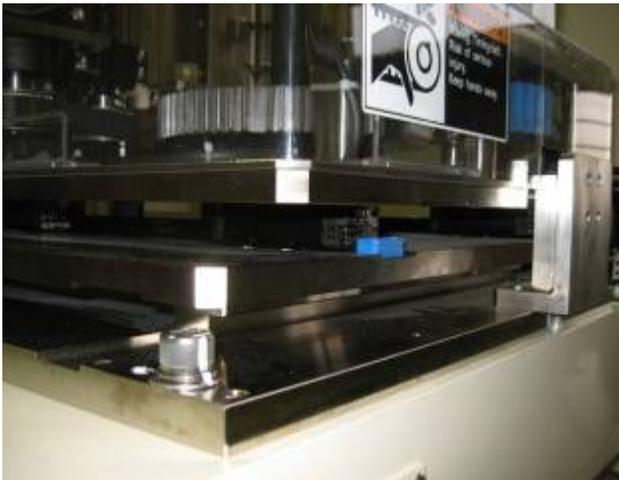
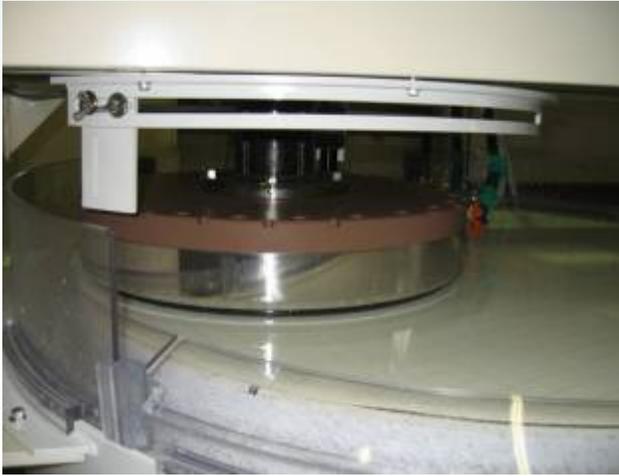
Change in Diamond Disc Surface Height



The interferometric analysis did not quantify diamond disc substrate wear accurately.

Wear Test Results

Araca APD – 800 Polisher & Tribometer



Experimental Conditions

– Pad

- 30-inch IC1000 A6 pad with Suba IV sub-pad

– Slurry

- 2 volume parts of Fujimi PL-7103 slurry + 8 volume parts of DI H₂O + 0.33 volume parts of 30% ultra pure H₂O₂
- 10 volume parts of Cabot Microelectronics Corporation iCue 600Y75 slurry + 1.1 volume parts of 30% ultra pure H₂O₂
- Flow rate = 250 ml/min

– Pad Conditioning

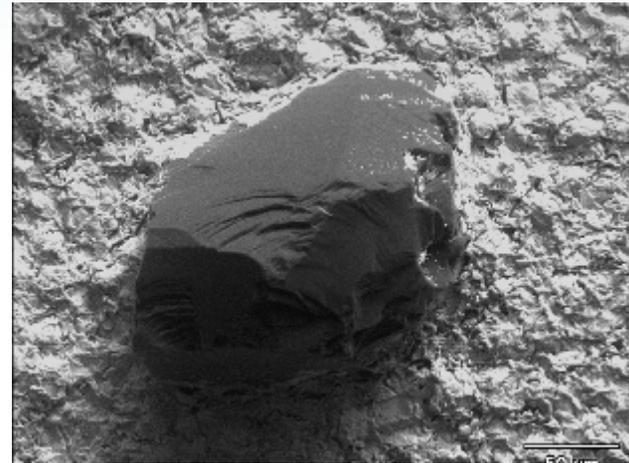
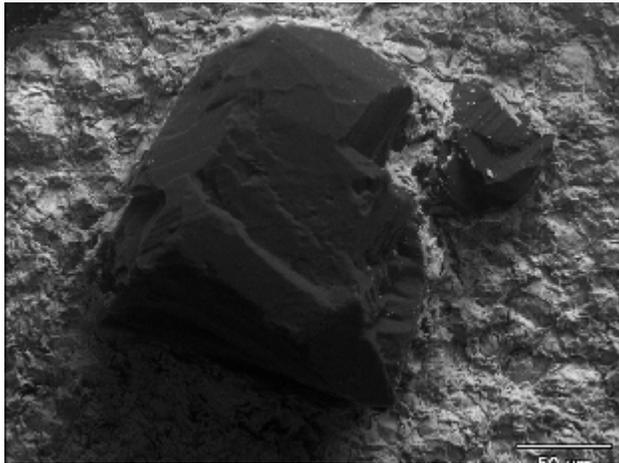
- Diamond disc rotational rate = 95 RPM
- Diamond disc sweeping rate = 10 times/min
- Platen rotational rate = 42 RPM
- Platen temperature = 25 °C
- Conditioning down force = 10 lb_f
- Conditioning time = 24 hours

No wafer polishing was performed during the wear test.

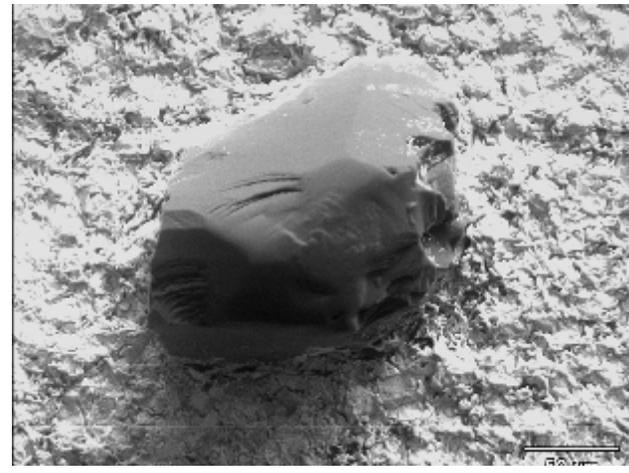
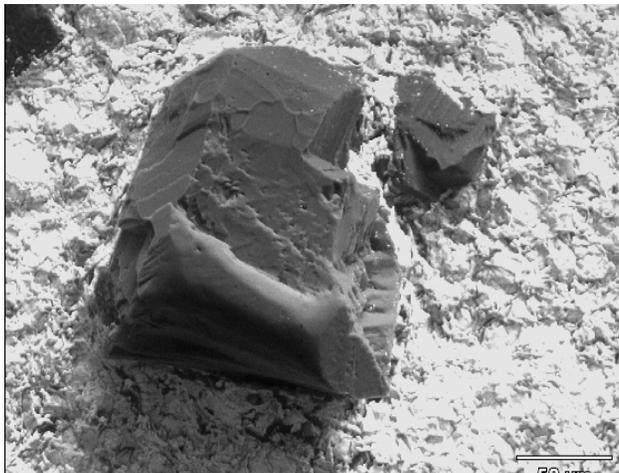
SEM Analysis – Aggressive Diamonds

D1 with CMC iCue 600Y75 Slurry at 25 °C

Before
Wear
Test



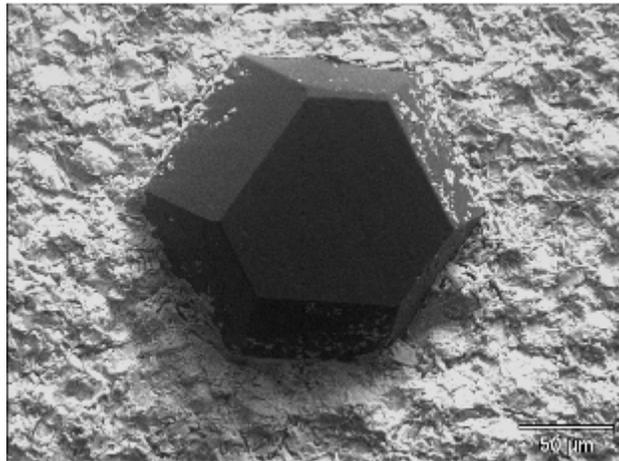
After
Wear
Test



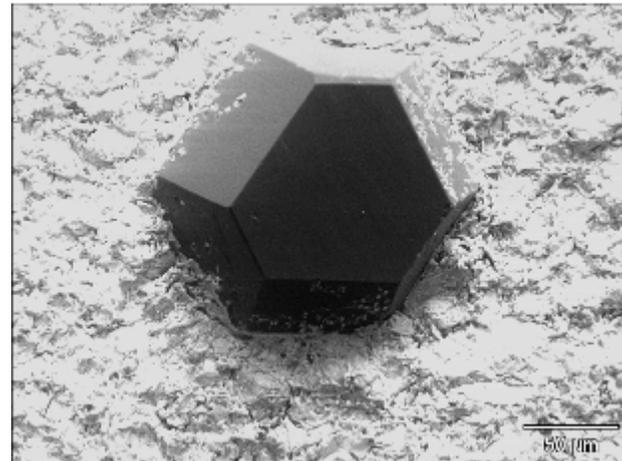
**There was micro wear on the cutting edges of aggressive diamonds.
There was no appreciable wear on the diamond disc substrate.**

SEM Analysis – Inactive Diamond D1 with CMC iCue 600Y75 Slurry at 25 °C

Before
Wear
Test



After
Wear
Test

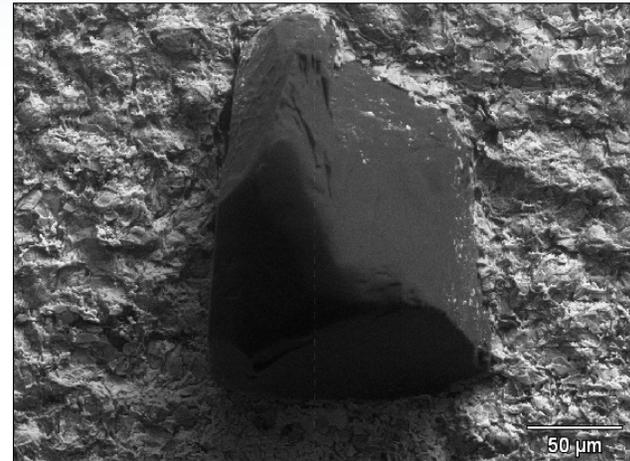
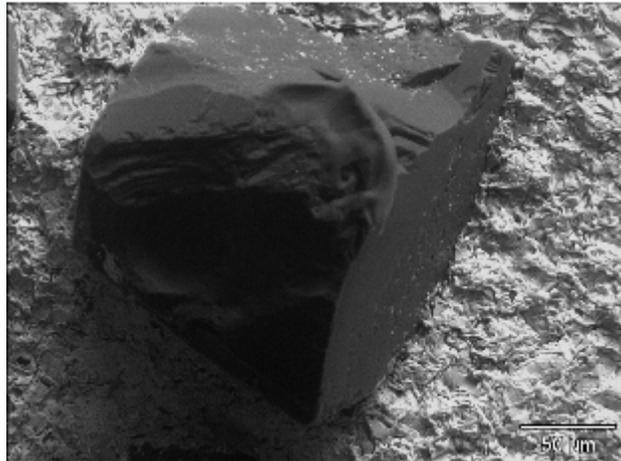


There was no appreciable wear on the inactive diamond and diamond disc substrate.

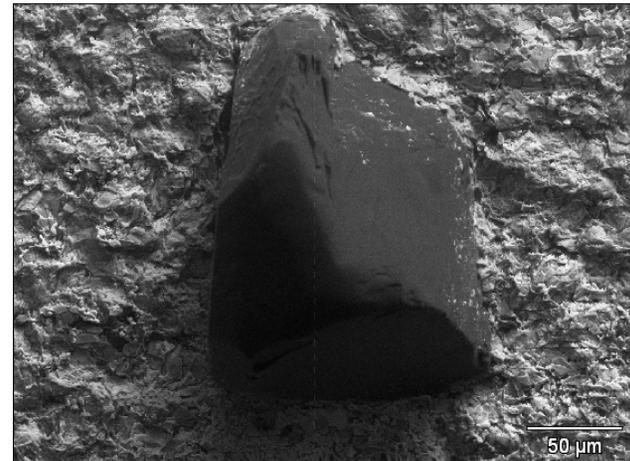
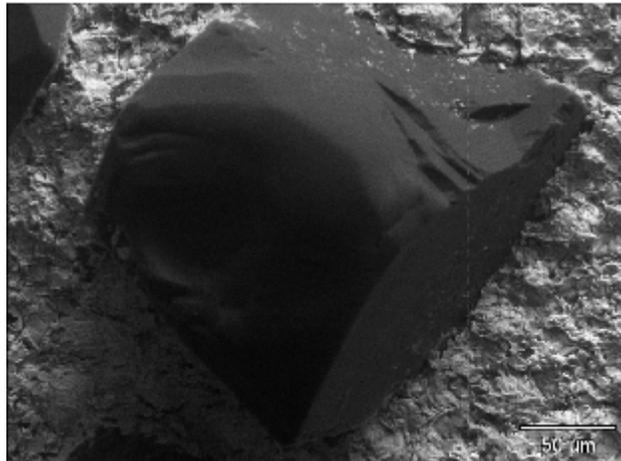
SEM Analysis – Aggressive Diamonds

D1 with CMC iCue 600Y75 Slurry at 50 °C

Before
Wear
Test



After
Wear
Test

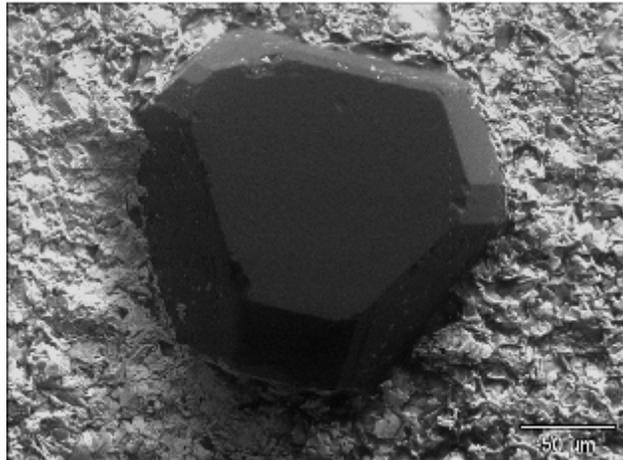


**There was micro wear on the cutting edges of aggressive diamonds.
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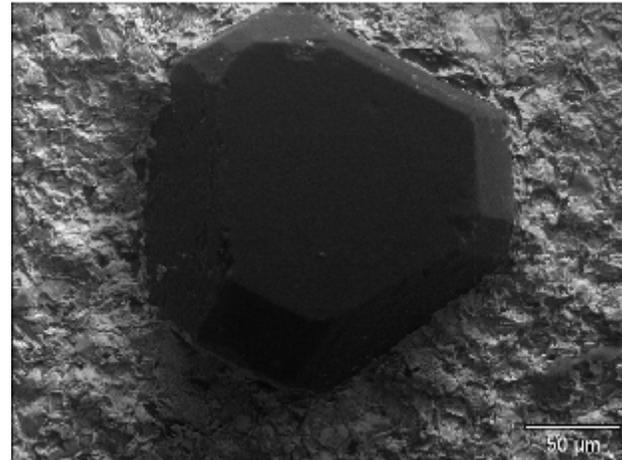
SEM Analysis – Inactive Diamond

D1 with CMC iCue 600Y75 Slurry at 50 °C

Before
Wear
Test



After
Wear
Test

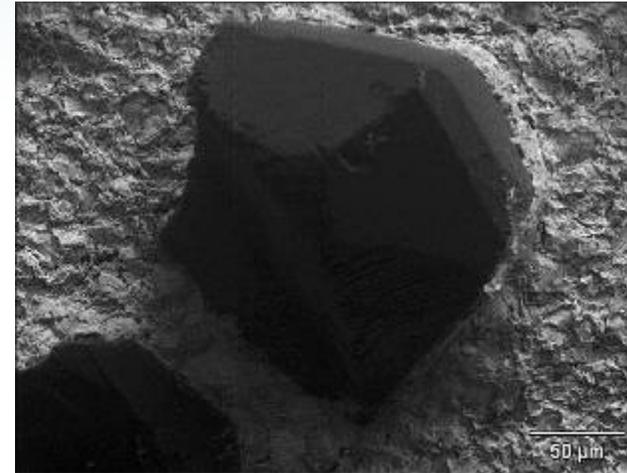
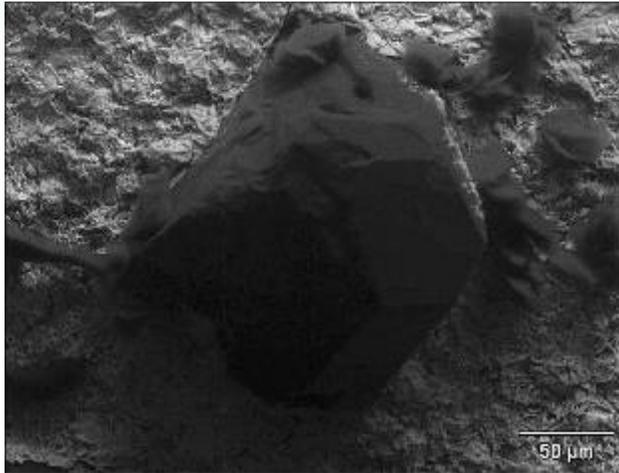


There was no appreciable wear on the inactive diamond and diamond disc substrate.

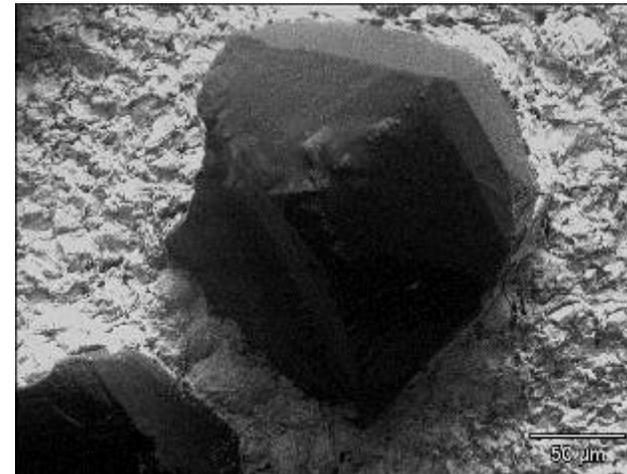
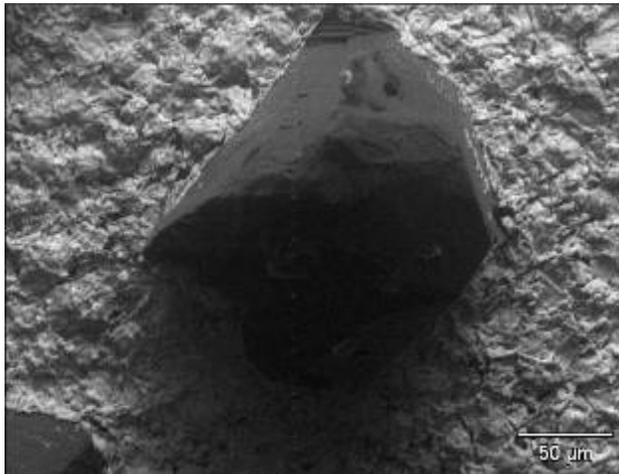
SEM Analysis – Aggressive Diamonds

D1 with Fujimi PL-7103 Slurry at 25 °C

Before
Wear
Test



After
Wear
Test

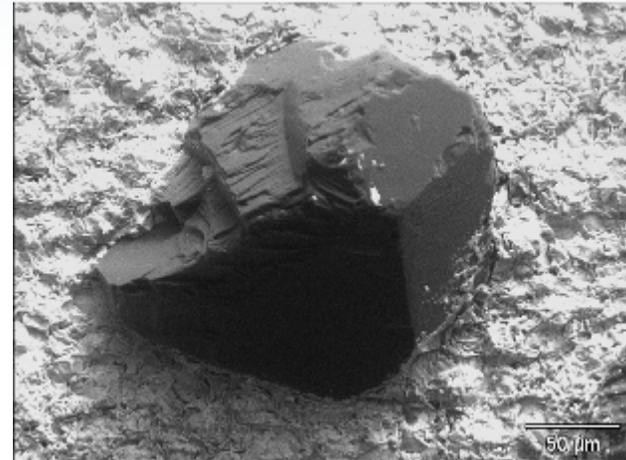
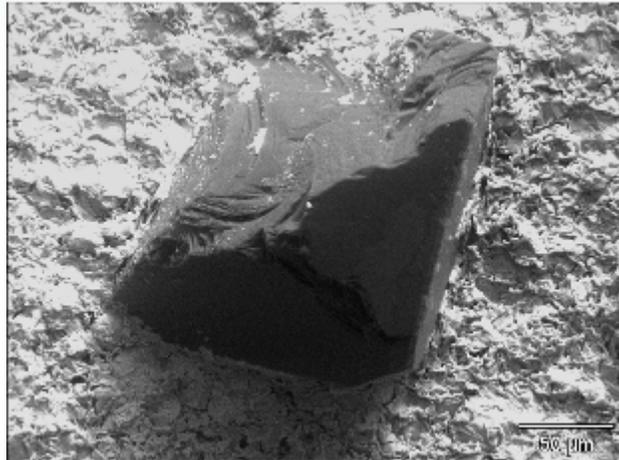


**There was micro wear on the cutting edges of aggressive diamonds.
There was no appreciable wear on the diamond disc substrate.**

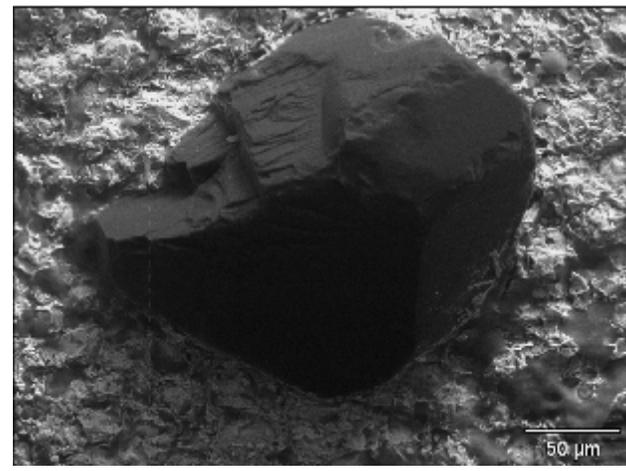
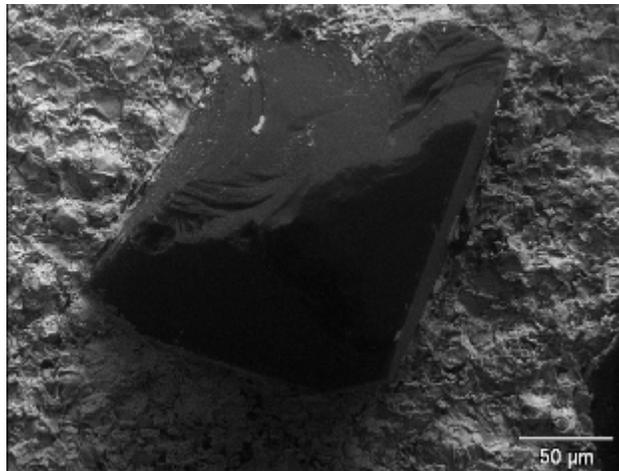
SEM Analysis – Aggressive Diamonds

D1 with Fujimi PL-7103 Slurry at 50 °C

Before
Wear
Test



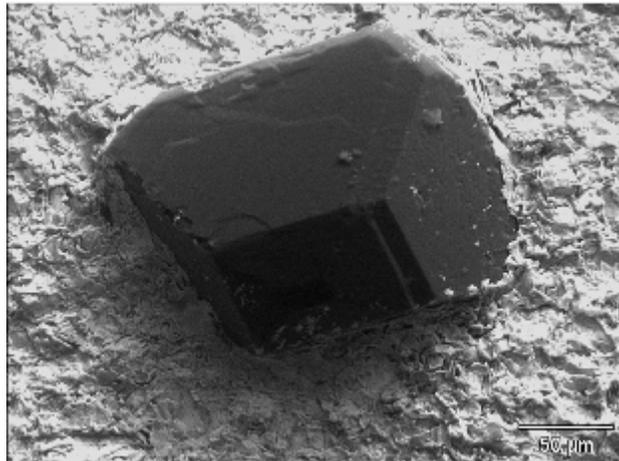
After
Wear
Test



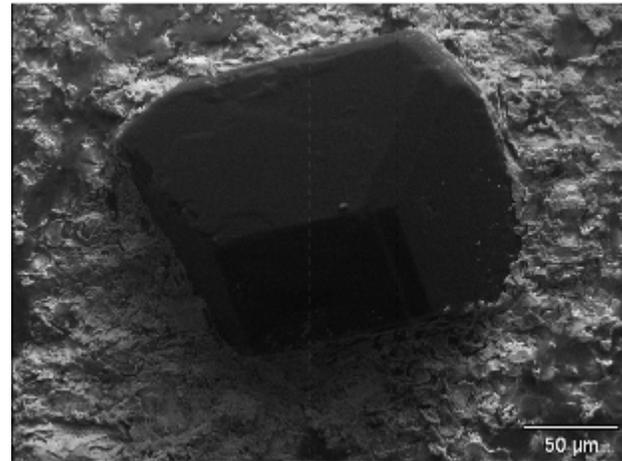
**There was micro wear on the cutting edges of aggressive diamonds.
There was no appreciable wear on the diamond disc substrate.**

SEM Analysis – Inactive Diamond D1 with Fujimi PL-7103 Slurry at 50 °C

Before
Wear
Test



After
Wear
Test

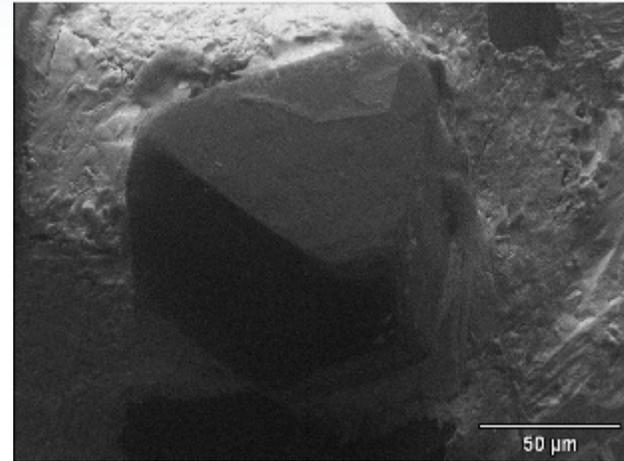
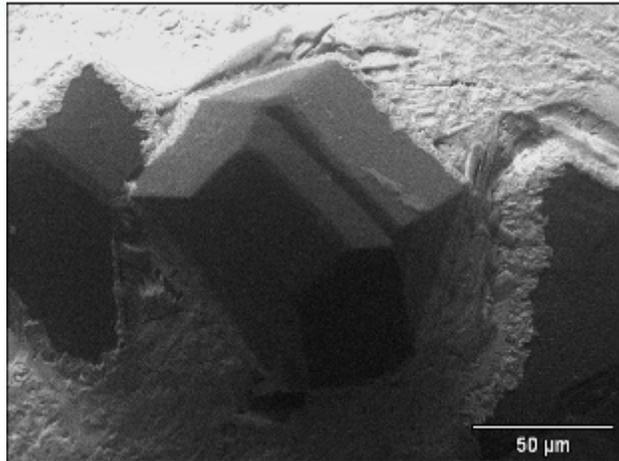


There was no appreciable wear on the inactive diamond and diamond disc substrate.

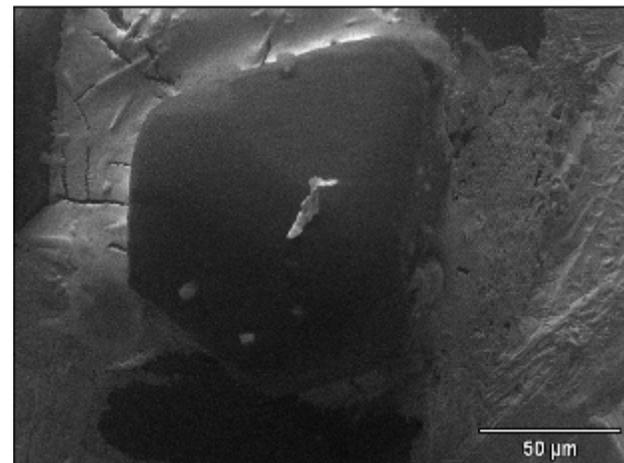
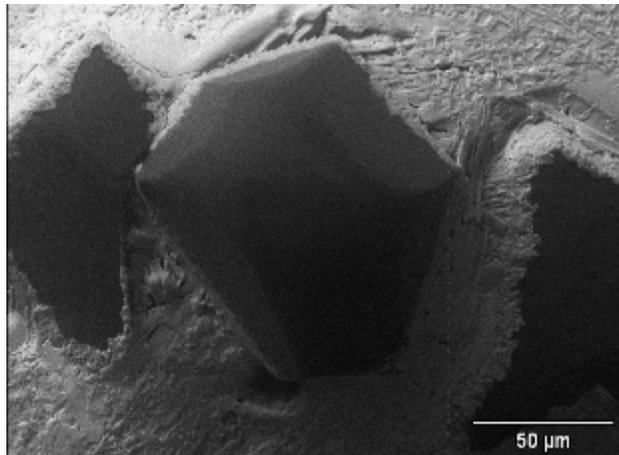
SEM Analysis – Aggressive Diamonds

D2 with CMC iCue 600Y75 Slurry at 25 °C

Before
Wear
Test



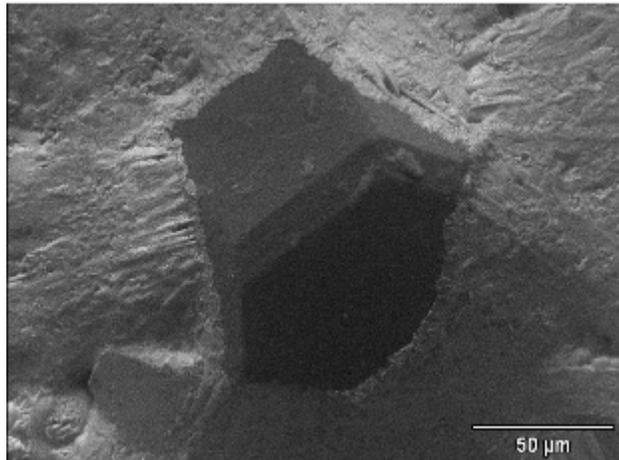
After
Wear
Test



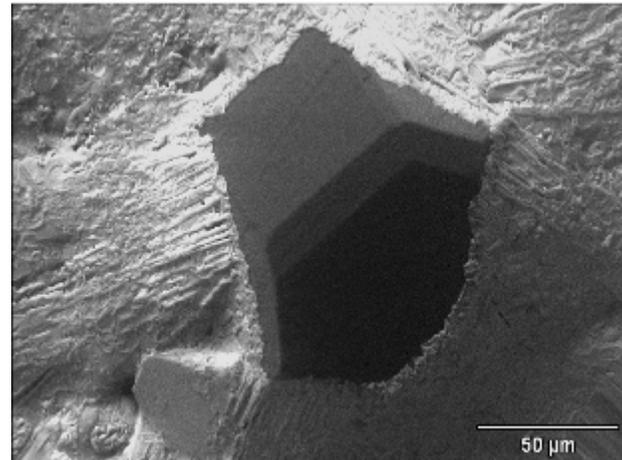
There was micro wear on the cutting edges of aggressive diamonds.
Micro cracks formed on the diamond disc substrate.

SEM Analysis – Inactive Diamond D2 with CMC iCue 600Y75 Slurry at 25 °C

Before
Wear
Test



After
Wear
Test

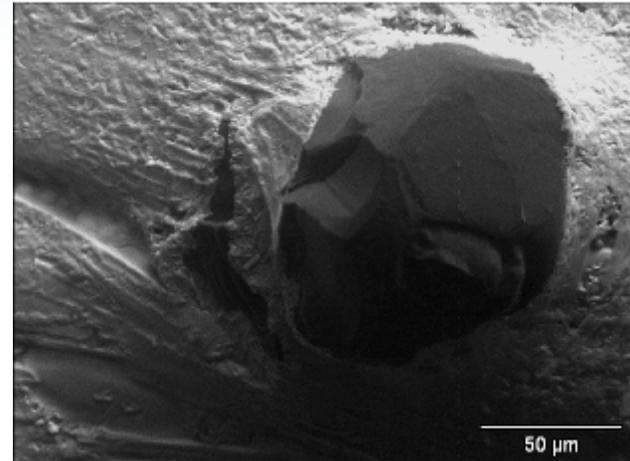
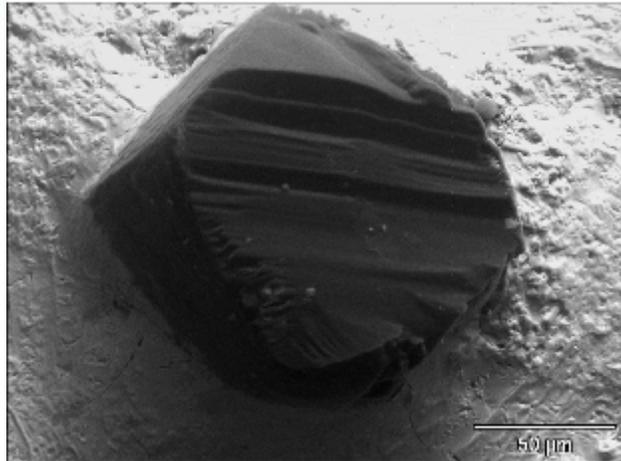


**There was no appreciable wear on the inactive diamond.
There was appreciable surface corrosion on the diamond disc substrate.**

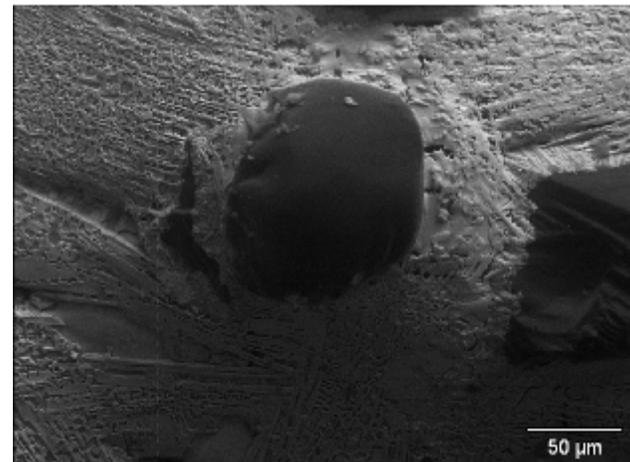
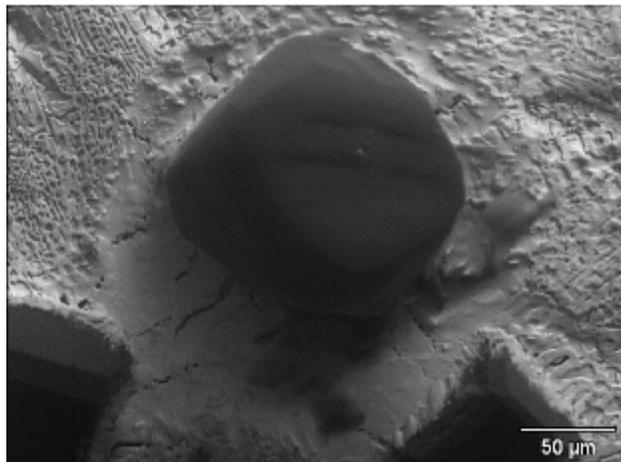
SEM Analysis – Aggressive Diamonds

D2 with CMC iCue 600Y75 Slurry at 50 °C

Before
Wear
Test



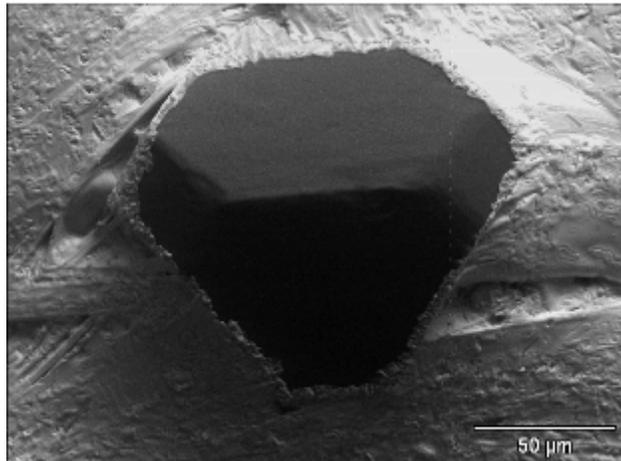
After
Wear
Test



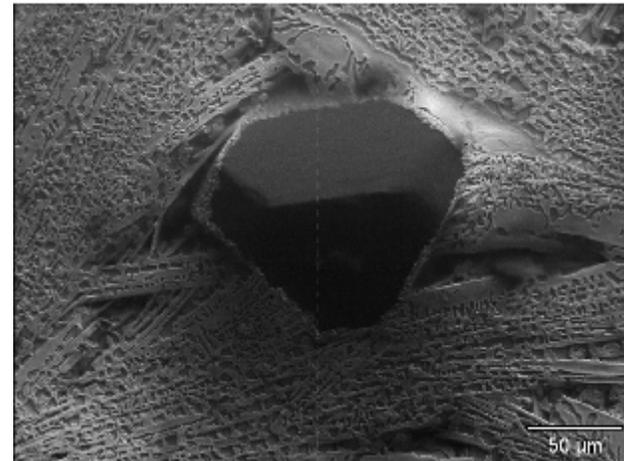
There was micro wear on the cutting edges of aggressive diamonds.
There was apparent surface corrosion on the diamond disc substrate.

SEM Analysis – Inactive Diamond D2 with CMC iCue 600Y75 Slurry at 50 °C

Before
Wear
Test



After
Wear
Test

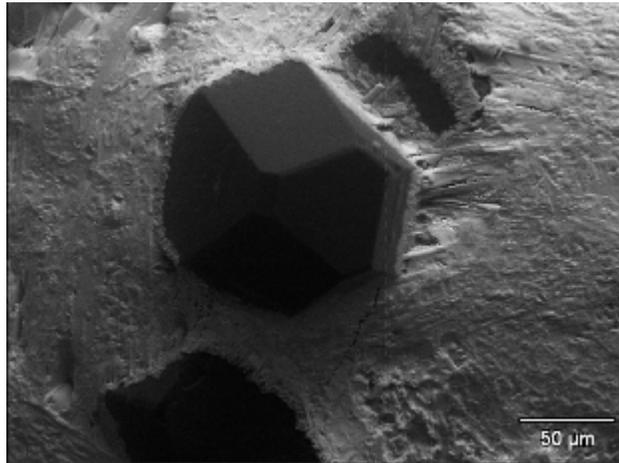


**There was no appreciable wear on the inactive diamond.
There was apparent surface corrosion on the diamond disc substrate.**

SEM Analysis – Aggressive Diamond

D2 with Fujimi PL-7103 Slurry at 25 °C

Before
Wear
Test



After
Wear
Test

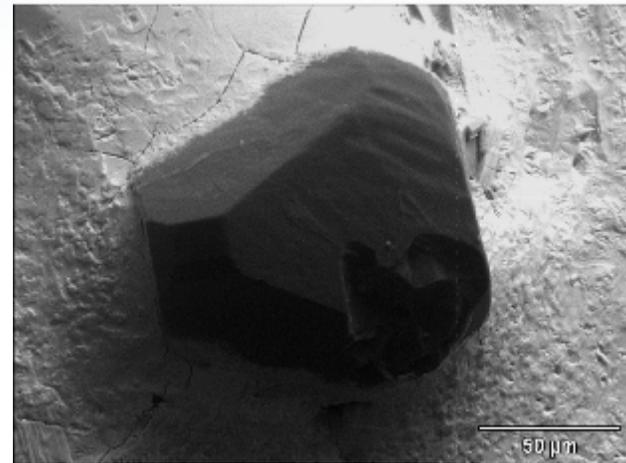
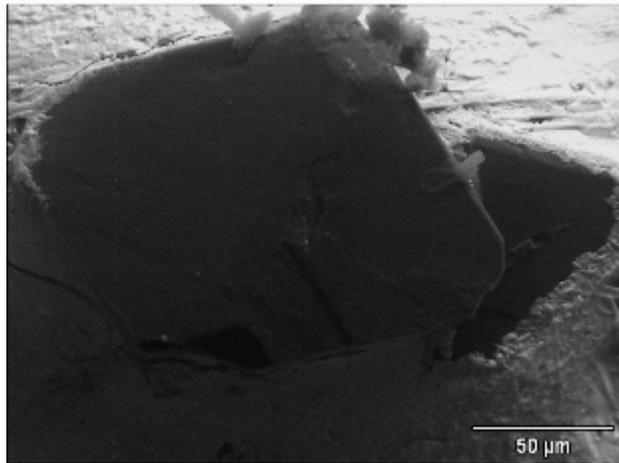


**There was micro wear on the cutting edges of aggressive diamond.
There was apparent surface corrosion on the diamond disc substrate.**

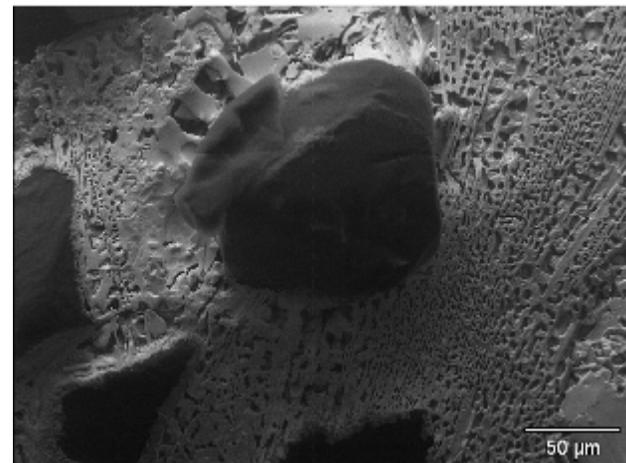
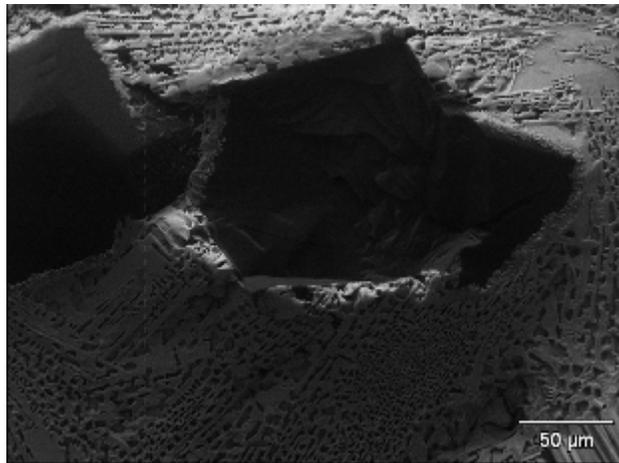
SEM Analysis – Aggressive Diamonds

D2 with Fujimi PL-7103 Slurry at 50 °C

Before
Wear
Test



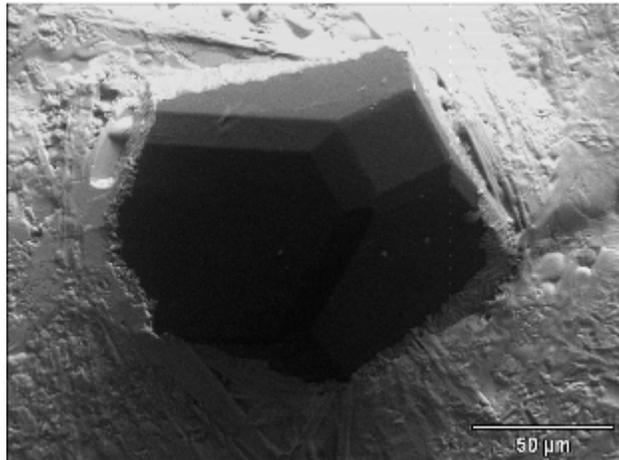
After
Wear
Test



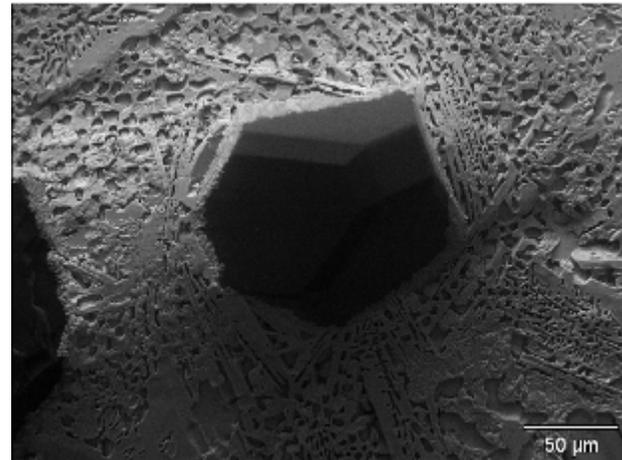
**One aggressive diamond broke from the diamond disc substrate.
There was micro wear on the cutting edges of the other aggressive diamond.
There was apparent surface corrosion on the diamond disc substrate.**

SEM Analysis – Inactive Diamond D2 with Fujimi PL-7103 Slurry at 50 °C

**Before
Wear
Test**



**After
Wear
Test**

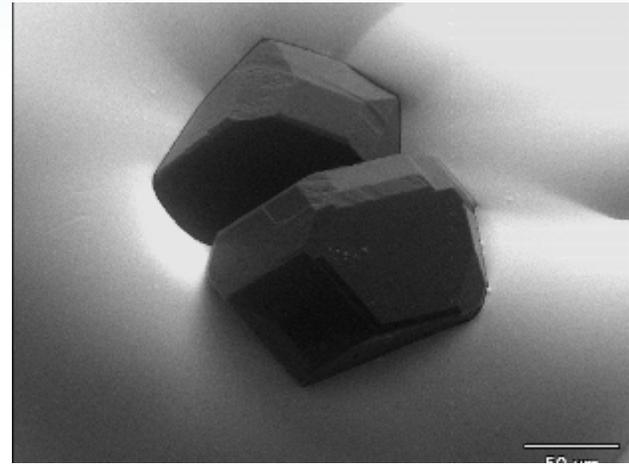
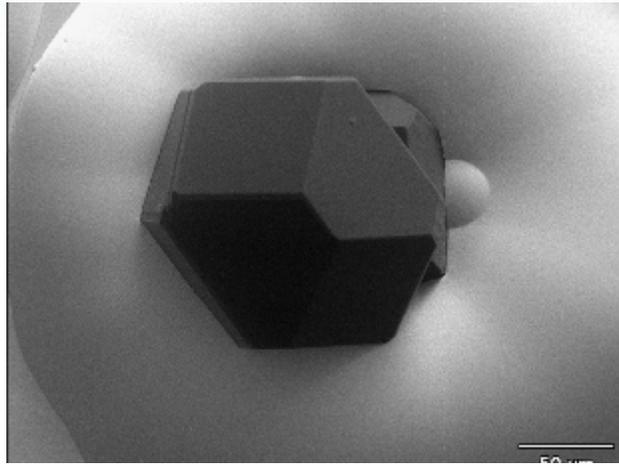


**There was no appreciable wear on the inactive diamond.
There was apparent surface corrosion on the diamond disc substrate.**

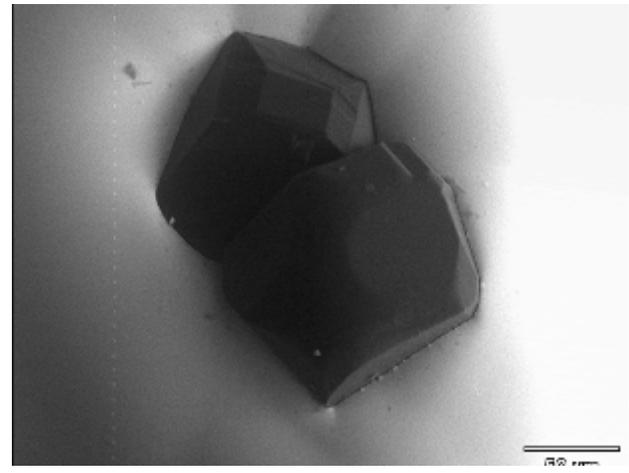
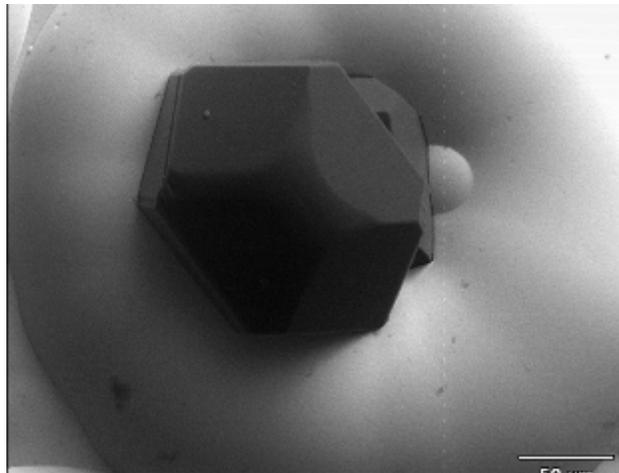
SEM Analysis – Aggressive Diamonds

D3 with CMC iCue 600Y75 Slurry at 25 °C

Before
Wear
Test



After
Wear
Test

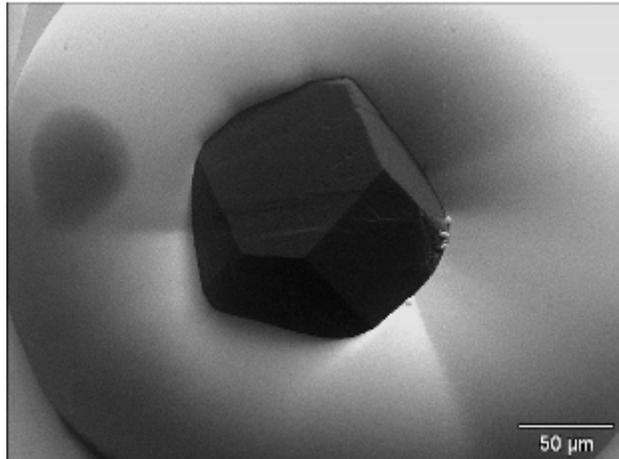


**There was micro wear on the cutting edges of aggressive diamonds.
There was no appreciable wear on the diamond disc substrate.**

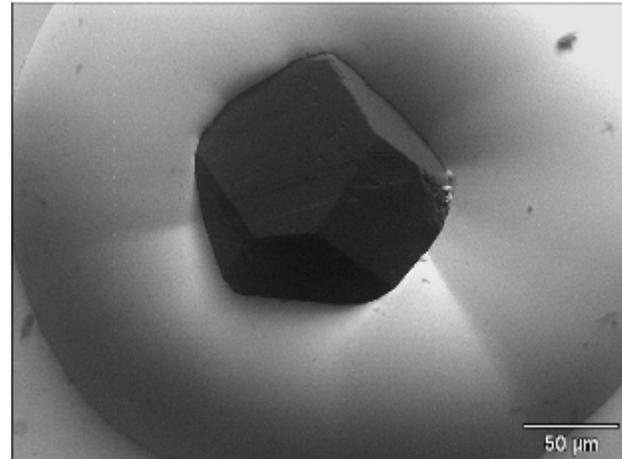
SEM Analysis – Inactive Diamond

D3 with CMC iCue 600Y75 Slurry at 25 °C

Before
Wear
Test



After
Wear
Test

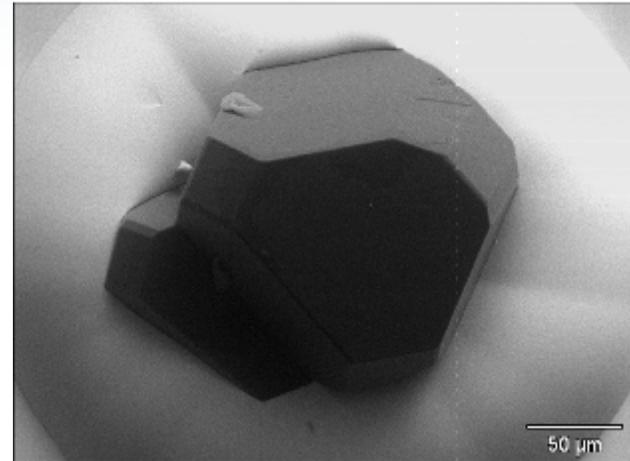
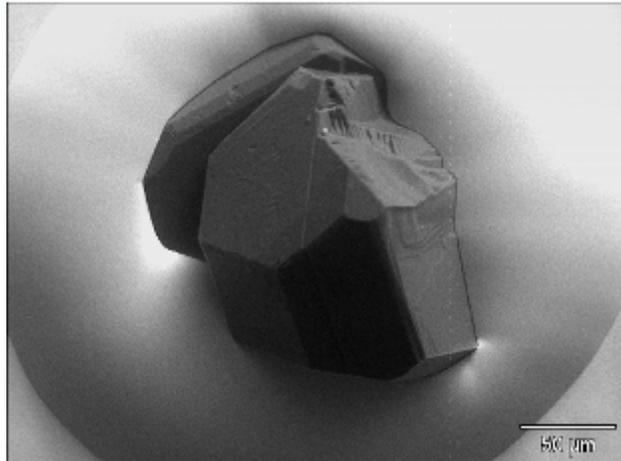


There was no appreciable wear on the inactive diamond and diamond disc substrate.

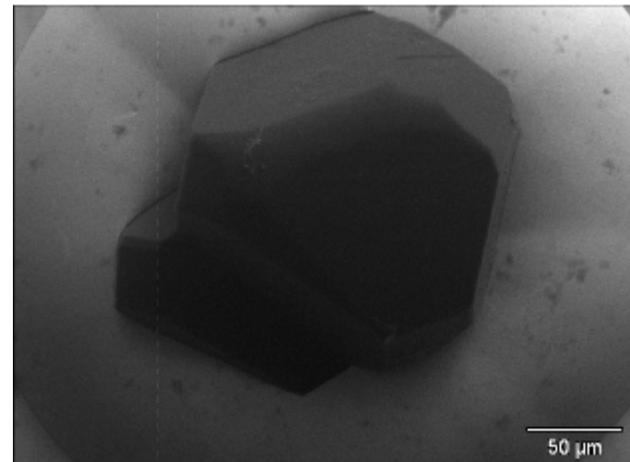
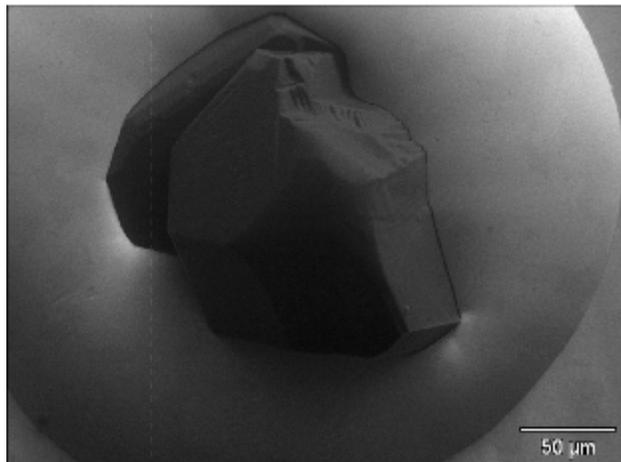
SEM Analysis – Aggressive Diamonds

D3 with CMC iCue 600Y75 Slurry at 50 °C

Before
Wear
Test



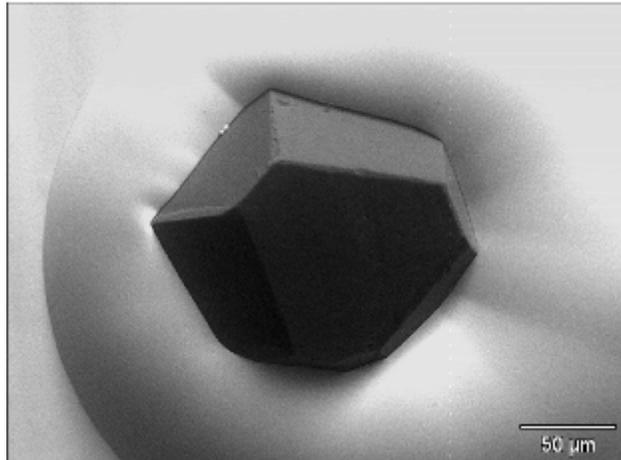
After
Wear
Test



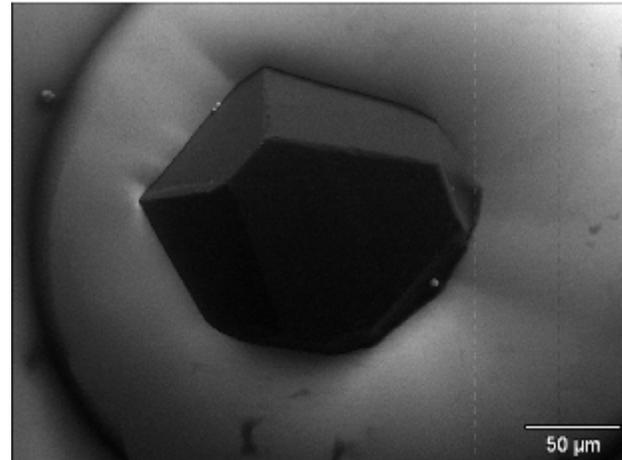
**There was micro wear on the cutting edges of aggressive diamonds.
There was no appreciable wear on the diamond disc substrate.**

SEM Analysis – Inactive Diamond D3 with CMC iCue 600Y75 Slurry at 50 °C

Before
Wear
Test



After
Wear
Test

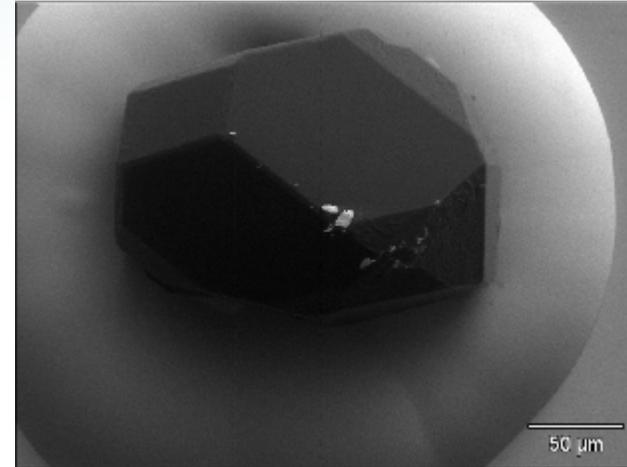
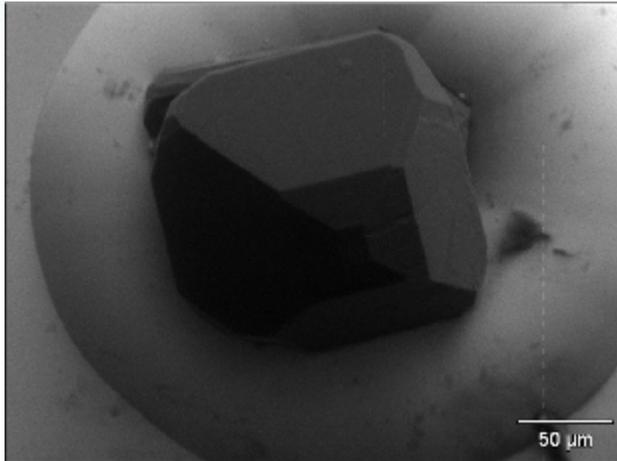


There was no appreciable wear on the inactive diamond and diamond disc substrate.

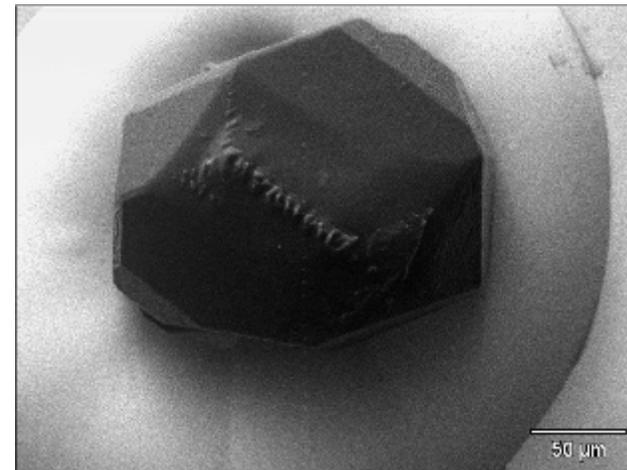
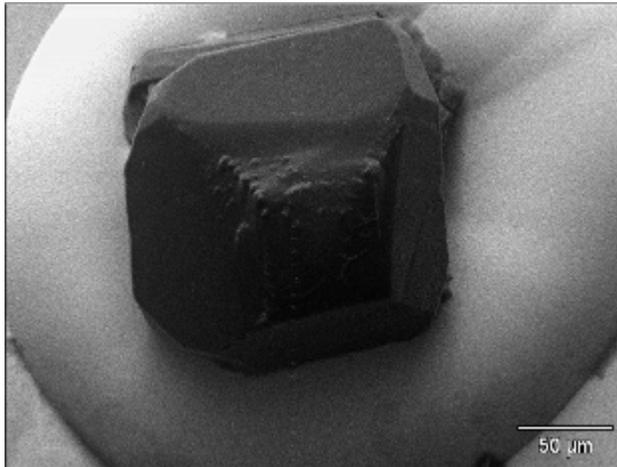
SEM Analysis – Aggressive Diamonds

D3 with Fujimi PL-7103 Slurry at 25 °C

Before
Wear
Test



After
Wear
Test

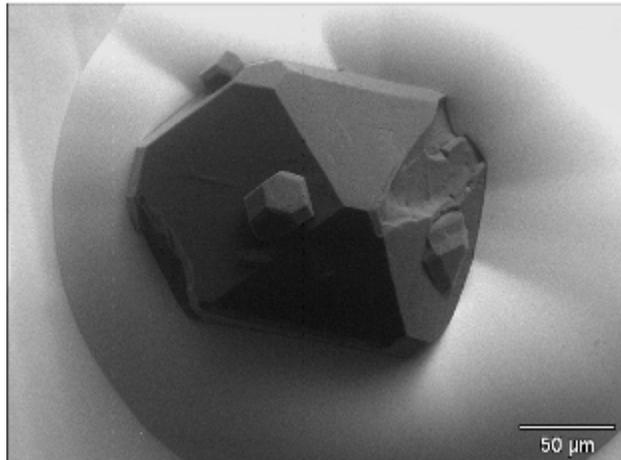


**There was micro wear on the cutting edges of aggressive diamonds.
There was no appreciable wear on the diamond disc substrate.**

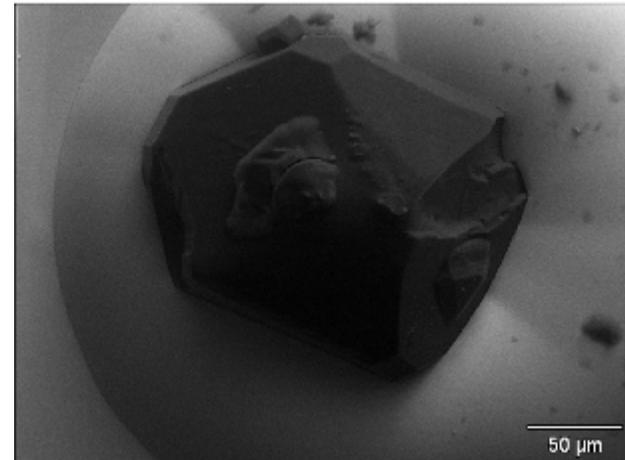
SEM Analysis – Aggressive Diamond

D3 with Fujimi PL-7103 Slurry at 50 °C

Before
Wear
Test



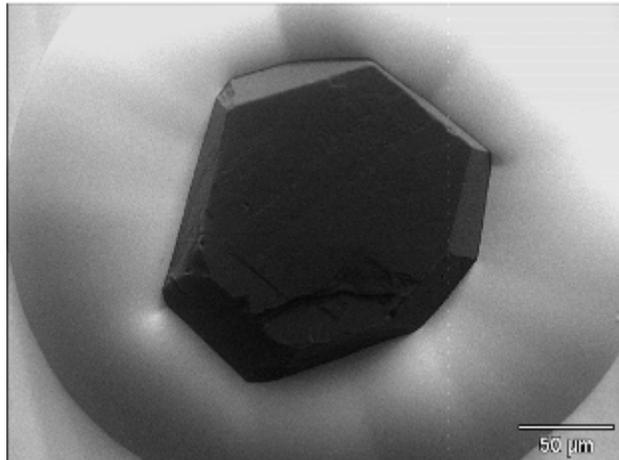
After
Wear
Test



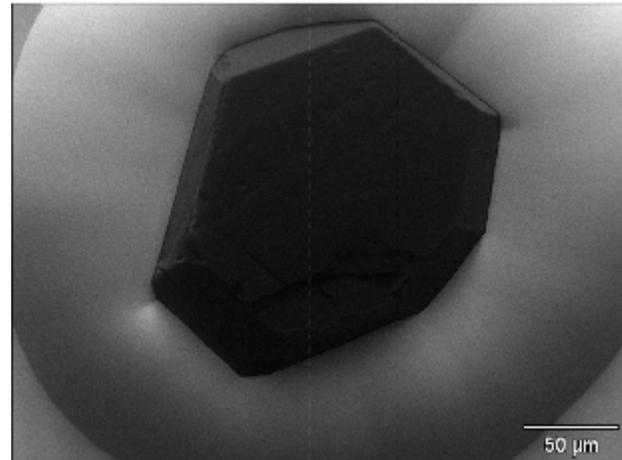
There was micro wear on the cutting edges of aggressive diamond.
There was no appreciable wear on the diamond disc substrate.

SEM Analysis – Inactive Diamond D3 with Fujimi PL-7103 Slurry at 50 °C

Before
Wear
Test



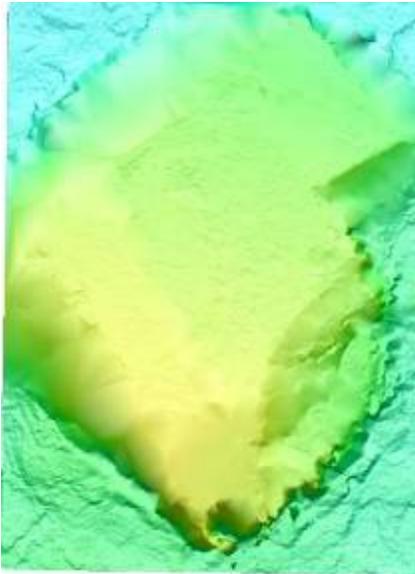
After
Wear
Test



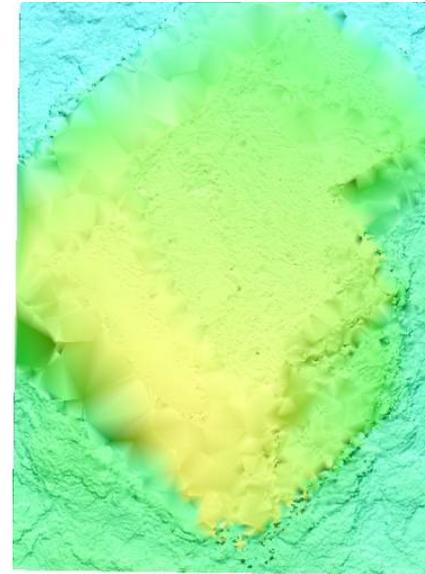
There was no appreciable wear on the inactive diamond and diamond disc substrate.

Interferometric Analysis – Aggressive Diamond

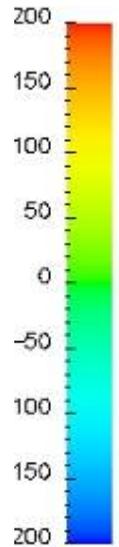
D1 with CMC iCue 600Y75 Slurry at 25 °C



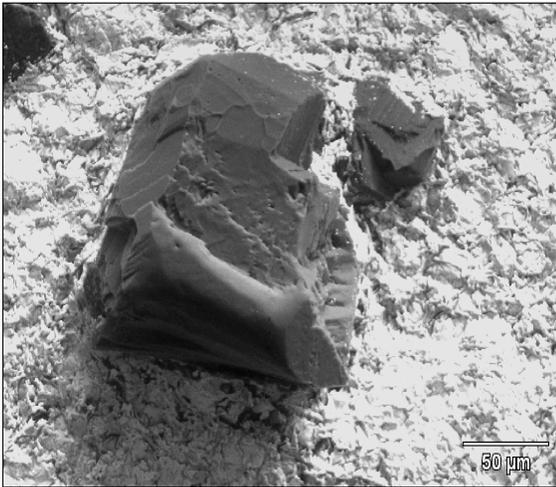
Before Wear Test



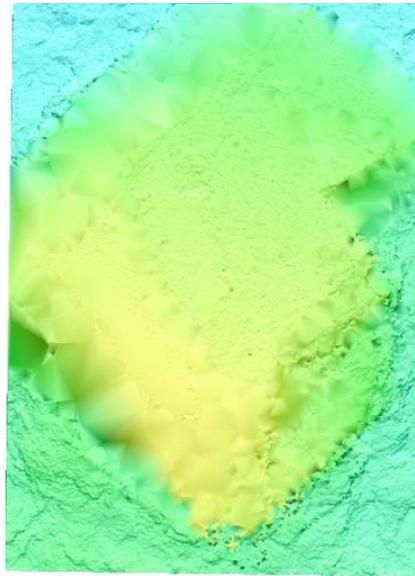
After Wear Test



SEM vs. Interferometer vs. Confocal Microscope



SEM Image



**Interferometric
Image**



**Confocal
Microscopic
Image**

Average Pad Cut Rate

Temperature	D1 ($\mu\text{m}/\text{hour}$)		D2 ($\mu\text{m}/\text{hour}$)		D3 ($\mu\text{m}/\text{hour}$)	
	Fujimi PL-7103	CMC iCue 600Y75	Fujimi PL-7103	CMC iCue 600Y75	Fujimi PL-7103	CMC iCue 600Y75
25 °C	14.33	3.03	7.87	2.32	6.05	0.93
50 °C	10.84	2.05	11.09	2.90	4.98	0.88

Summary

Static Etch Tests – SEM Analysis

		D1		D2		D3	
		Fujimi PL-7103	CMC iCue 600Y75	Fujimi PL-7103	CMC iCue 600Y75	Fujimi PL-7103	CMC iCue 600Y75
25 °C	Diamond	No appreciable wear					
	Diamond Disc Substrate	No appreciable wear		Apparent surface corrosion	No appreciable wear	No appreciable wear	
50 °C	Diamond	No appreciable wear					
	Diamond Disc Substrate	No appreciable wear		Apparent surface corrosion		No appreciable wear	

Static Etch Tests – ICPMS and Interferometric Analysis

With Fujimi PL-7103 slurry, ICPMS analysis indicated that the Ni concentration in the slurry increased appreciably at 25 and 50 °C for Disc D1; the Ni concentration in the slurry increased significantly at 25 °C and increased dramatically at 50 °C for Disc D2.

With CMC iCue 600Y75 slurry, ICPMS analysis indicated that the Ni concentration in the slurry increased appreciably at 25 and 50 °C for Disc D1; the Ni concentration in the slurry increased appreciably at 25 °C and increased dramatically at 50 °C for Disc D2, resulting in an extremely high activation energy for Ni corrosion.

ICPMS analysis indicated that for both Fujimi PL-7103 and CMC iCue 600Y75 slurries, there was barely any increase in the Ni concentration in the slurry at 25 and 50 °C for Disc D3.

White light interferometer did not provide as detailed and accurate diamond disc images as SEM. As a result, the interferometric analysis did not quantify diamond disc substrate wear accurately.

Wear Tests – SEM Analysis

		D1		D2		D3	
		Fujimi PL-7103	CMC iCue 600Y75	Fujimi PL-7103	CMC iCue 600Y75	Fujimi PL-7103	CMC iCue 600Y75
25 °C	Aggressive Diamond	Micro wear on cutting edges					
	Inactive Diamond	No appreciable wear					
	Diamond Disc Substrate	No appreciable wear		Apparent surface corrosion		No appreciable wear	
50 °C	Aggressive Diamond	Micro wear on cutting edges		Micro wear on cutting edges / broken diamond		Micro wear on cutting edges	
	Inactive Diamond	No appreciable wear					
	Diamond Disc Substrate	No appreciable wear		Apparent surface corrosion		No appreciable wear	

Wear Tests – Pad Wear Rate and Interferometric Analysis

The pad wear rate analysis indicated that:

For both Fujimi PL-7103 and CMC iCue 600Y75 slurries at 25 °C, Disc D1 generated the highest pad wear rate while Disc D3 generated the lowest pad wear rate. On the other hand, Disc D2 generated the highest pad wear rate while Disc D3 generated the lowest pad wear rate for both slurries at 50 °C.

For both Fujimi PL-7103 and CMC iCue 600Y75 slurries, the pad wear rate decreased with the increase of the platen temperature for Disc D1 and Disc D3. On the other hand, the pad wear rate increased with the platen temperature for Disc D2 for both slurries.

For all three types of discs, the pad wear rate for Fujimi PL-7103 slurry was significantly higher than CMC iCue 600Y75 slurry, indicating slurry abrasives and abrasive concentration have significant impacts on the pad wear rate.

As the white light interferometer did not capture the cutting edges of individual diamonds and the boundaries between embedded diamonds and disc substrate, the interferometric analysis did not quantify diamond micro-wear accurately.

Acknowledgements

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Cabot Microelectronics Corporation

Fujimi Corporation

Rohm and Haas